HIGH TEMPERATURE UF6 RF PLASMA EXPERIMENTS
APPLICABLE TO URANIUM PLASMA CORE REACTORS

Ward C. Roma-
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An experimental and analytical investigation was conducted using the United Technologies Research Center (UTRC) 1.2 MW rf induction heater facility to aid in developing the technology necessary for designing a self-critical fissioning uranium plasma core reactor (PCR). Pure, high temperature uranium hexafluoride (UF₆) was injected into an argon fluid-mechanically-confined, steady-state, rf-heated plasma while employing different exhaust systems and diagnostic techniques to simulate and investigate some potential characteristics of uranium plasma core nuclear reactors.

The objectives of this follow-on research were: (1) to continue the development of techniques and equipment for fluid mechanical confinement of rf-heated uranium plasmas with a high density of uranium vapor within the plasma while simultaneously minimizing deposition of uranium and uranium compounds on the test chamber peripheral wall, endwall surfaces, and primary exhaust ducts; (2) continue to develop and test materials and handling techniques suitable for use with high-temperature, high-pressure, gaseous UF₆; and (3) to continue development of complementary diagnostic instrumentation and measurement techniques to characterize the uranium plasma, effluent exhaust gases, and residue deposited on the test chamber and exhaust system components. In preparation for near-term interfacing of the UF₆ rf-heated plasma experiments with downstream separator/reprocessing systems, emphasis was also placed on development of a primary exhaust system capable of transporting the UF₆ effluent exhaust gas to the downstream traps with minimum uranium compound wall deposition.

The test configuration used in the majority of tests employed a water-cooled, fused-silica cylindrical test chamber. The test chamber peripheral wall was 5.7-cm-ID by 10-cm-long. The radial inflow vortex was driven by injectors located on one endwall. In addition to a centerline exhaust thru-flow duct, an axial bypass annulus was located near the periphery. This test chamber flow configuration was designed to operate at pressures up to 20 atm and rf discharge power levels up to approximately 100 kW. The pure UF₆ was supplied to the endwall on-axis injector from a heated canister system capable of supplying the gaseous UF₆ at temperatures up to 450 K and pressures up to 20 atm.
The different exhaust systems employed in the tests included: provision for varying the temperature of the individual endwalls and primary exhaust duct sections, and the use of a porous exhaust duct assembly incorporating a diluent bleed radial flow injection. These schemes were used to aid in reducing the wall coatings due to uranium compound deposition.

Diagnostic measurements included exhaust gas sampling using both off- and on-line IR spectrophotometric absorption and Time-of-Flight (T.O.F.) mass spectrometer techniques. In selected tests, a residue analysis was conducted on the material deposited on the various key components of the test chamber and exhaust system.

Supporting studies included: continued development of uranium compound reference standards using six different complementary diagnostic techniques for use in post-test characterization of the residue; continued research on the corrosion/contamination aspects of hot, pressurized UF₆; and a heat and mass transfer analysis of swirling hot flow within a porous duct with bleed flow augmentation.

The overall test results have demonstrated the feasibility of employing on-line diagnostic techniques to measure the concentration of UF₆ at different locations in the exhaust system. Results of hot flow tests with pure UF₆ injection indicated that the quantity and composition of the residue deposited on the surfaces of the different components of the test chamber and exhaust system were affected by the component surface temperature and the contamination levels of oxygen and water in the test gases. Operating the test components at a high temperature and using appropriate traps and getters on the inlet gas systems resulted in a significant reduction in the residue coatings; similar reductions were also achieved using flow augmentation in the primary exhaust duct system. In selected tests employing a porous Monel interstage exhaust duct assembly with argon transpiration flow, the absolute level of uranium compound residue found on the exhaust duct surface in post-test analysis was reduced three (3) orders of magnitude (to typically hundreds of microgram range equivalent to approximately 3 μg/cm² of exposed surface) compared to prior tests under comparable test conditions. This level of coating approached the detectability limit of the available measurement techniques. There are several reasons for trying to prevent deposition of fuel/fission products on the exhaust duct of an actual device. These include: cooling problems associated with the fuel deposition hot spots and associated structural problems; undesirable localized regions of high dose rate radiation; and requirement to remove fuel/fission products to selected reprocessing components downstream of the actual cavity where efficient reprocessing can occur.

The results obtained from long run times indicate about 13 percent of the total UF₆ injected into the rf plasma test chamber was deposited out on the components upstream of the main cold trap system. Less than 0.1 percent was deposited within the confines of the rf plasma test chamber; approximately 0.6 percent was deposited within the axial bypass exhaust duct. The residue was determined to consist primarily of UF₄ and UO₂F₂.
These results indicate the option now exists for future tests wherein a very large fraction of the total UF$_6$ injected into the test chamber (\( \approx 99.9 \) percent) can be made available for recovery/regeneration back to UF$_6$ using an exhaus. trap system with minimal uranium compound losses to the walls of the test chamber, axial bypass duct, and primary exhaust duct system. Simultaneous with this can be the on-line measurement of the UF$_6$ concentration within different sections of the exhaust system using an improved T.O.F. mass spectrometer system of the type employed in the UF$_6$ rf plasma tests.
Results and Conclusions

RF plasma tests with pure UF₆ injection using the UTRC 1.2 MW induction heater system, different exhaust systems, and various diagnostic techniques yielded the following results.

1. Results from tests conducted over test times of up to about eleven minutes and using selected configurations and flow techniques indicated that less than 0.1 percent of the total UF₆ initially injected into the rf plasma test chamber was deposited on the test chamber itself; approximately 0.6 percent was deposited within the axial bypass exhaust duct. Of the total UF₆ injected, 43 g, about 13 percent was deposited out on the components upstream of the main cold trap system where future UF₆ regeneration schemes can be applied to eliminate the wall coating. The remainder reached the cold trap system where efficient reprocessing can be accomplished.

2. Employing independent cooling control of the different components of the test chamber and exhaust system has aided in significantly reducing the residue coatings (e.g., early test results indicated typically several hundred milligrams of primarily UO₂F₂ and UF₄ was uniformly deposited on the endwall surfaces -- 8 mg/cm² of endwall area). By operating the endwalls at as high a temperature as possible (≤800 K), subject to heat transfer limitations, the residue coating was reduced to levels of nominally 1-10 mg (0.04-0.4 mg/cm²). Similarly, by throttling down the water cooling supplied to the interstage exhaust duct system, comparable reductions in residue wall coating were achieved.

3. Incorporation of filter traps and getters on the gas inlet systems to eliminate the O₂ and H₂O impurities has aided in reducing the formation of the oxides of uranium and also contributed in reducing the magnitude of residue deposition on the test components.

4. Use of different flow augmentation schemes immediately upstream of the interstage exhaust duct resulted in an approximate order of magnitude reduction in the residue wall coating.

5. Tests employing a porous (≈5 μm-dia nominal pore size) Monel exhaust duct system demonstrated the feasibility of employing radial transpiration injection of argon gas as a means for significantly reducing the post-test uranium compound wall coating. In several controlled tests, the quantity of residue was reduced by a factor of approximately 3000 compared to earlier test results not employing the porous exhaust duct scheme. The hundreds of microgram levels achieved (equivalent to approximately 3 μg/cm² of exposed surface) approached the detectability limit of the available measurement techniques; the maximum UF₆ mass thru-put employed in these tests was 43 g.
6. The continued development of complementary diagnostic instrumentation and measurement techniques to characterize the effluent exhaust gases resulted in the demonstration of two techniques applicable for use in future exhaust gas sampling measurements. One scheme is optical, involving the use of an IR spectrophotometer and absorption cell; the other scheme employed a modified commercially available T.O.F. mass spectrometer, sampling probe system. The feasibility of using either system in an off- or on-line mode of operation was demonstrated and the test results obtained using both systems under similar test conditions were in reasonable agreement. Based on several inherent advantages, the T.O.F. system is recommended over the IR absorption scheme. Two of the key advantages are: the ability to rapidly scan over a wide spectral range to provide analysis of both major and minor species; and, provide quantitative data on the radial UF₆ concentration distribution within different sections of the exhaust system.

7. Test results obtained using the IR spectrophotometer absorption and gas sampling system indicated no trace of UF₆ was detected in the axial bypass exhaust duct system in any of the tests. The T.O.F. mass spectrometer and gas sampling system indicated low concentrations (<500 ppm*) of UF₆ were present on the centerline of the axial bypass exhaust duct system. This is encouraging from the standpoint of minimizing the complexity of the exhaust gas collection and reprocessing systems required in future closed-loop PCR systems; it is also significant because it provides a quantitative measure of the uranium confinement characteristics of the vortex flow employed in the plasma test chamber.

8. Various complementary diagnostic techniques were employed for identifying and quantifying the small amounts of uranium compound residue deposited onto the different components of the test chamber and exhaust duct system. These techniques included use of the electron microscope, scanning electron microprobe, IR spectrophotometer, x-ray diffractometer, ion scattering spectrometer, and secondary ion mass spectrometer. The residue, which was uniformly deposited (not plated) on the walls of the exhaust system was determined to be primarily UF₄ and UO₂F₂.

9. An initial heat and mass transfer analysis of swirling flow within a porous duct with bleed flow augmentation was completed. Within the range of flow conditions of interest the results indicate the diffusion of the uranium compounds toward the wall can be counterbalanced by the radial transpiration injection of the bleed gas through the porous wall. This was also demonstrated in the experimental results.

10. Throughout this research effort, valuable data were also accumulated on the corrosion aspects of hot, pressurized UF₆ in a regime where very little published information is available. Included was an extended compilation of uranium compound reference standards for use in future post-test residue compound identification. The majority of these standards included the U-O-F compounds.

*Lower detectability limit of existing gas sampling system and T.O.F. mass spectrometer.
Uranium nuclear reactors which employ gaseous fissile fuel can be operated at high temperatures; this leads conceptually to power conversion systems for space and terrestrial applications with performance characteristics and thermodynamic cycle efficiencies significantly improved over conventional solid fuel element nuclear reactors. In addition to aerospace propulsion applications, several new space power and/or terrestrial options are being considered, some of which use the direct coupling of energy in the form of electromagnetic radiation. These include:

1. Direct pumping of lasers by fission fragment energy deposition in UF\textsubscript{6} and lasing gas mixtures;

2. Optical pumping of lasers by thermal and/or nonequilibrium electromagnetic radiation from fissioning UF\textsubscript{6} and/or fissioning uranium plasmas;

3. Photochemical or thermochemical processes such as dissociation of hydrogenous materials to produce hydrogen;

4. MHD power conversion systems for generating electricity; and

5. Advanced closed-cycle gas turbine driven electrical generators.

The continuous reprocessing of gaseous nuclear fuel also leads to a low steady-state fission product inventory in the reactor and limits the buildup of long half-life transuranium elements. This, together with the low critical mass, could result in increased safety and higher nuclear fuel resource utilization. References 1, 2, and 3 summarize various reactor concepts, designs, principles of operation, applications, and associated performance estimates.

A principal technology required to establish the feasibility of fissioning uranium plasma core reactors is the fluid mechanical confinement of the hot fissioning uranium plasma with sufficient containment to both sustain nuclear criticality and minimize deposition of uranium or uranium compounds on the confinement chamber peripheral walls. Figure 1 is a sketch of one unit cell configuration of a plasma core reactor (PCR). The reactor would consist of one or more such cells imbedded in beryllium oxide and/or heavy-water moderator and surrounded by a pressure vessel. In the central plasma fuel zone, gaseous uranium (injected in the form of UF\textsubscript{6} or other uranium compound) is confined by argon buffer gas injected tangentially at the periphery of the cell. UF\textsubscript{6} is a stable volatile gas at fuel injection temperatures and pressures of interest for plasma core reactors. Section AA at the bottom of Fig. 1 shows the UF\textsubscript{6} inlet and the on-axis and axial bypass exhaust ducts. The mixture of nuclear fuel and argon buffer gas is withdrawn from one or both endwalls at the axial centerline.
In applications in which it is desired to couple thermal radiation from the fissioning uranium plasma to a separate working fluid, the thermal radiation is transmitted through the argon buffer gas layer and, subsequently, through internally-cooled transparent walls to a working fluid channel such as shown in Fig. 1. The channels would contain particles, graphite fins, or opaque gases to absorb the radiation. For nonequilibrium, fission-fragment-induced short wavelength radiation emission applications, the working fluid channel would be removed and lasing gas mixtures would be mixed with either the uranium fuel or the buffer gas.

A long-range program plan to establish the feasibility of fissioning gaseous UF₆ and uranium plasma reactors has been formulated by NASA. Reference 4 summarizes the plan which comprises a series of experiments with reflector-moderator cavity reactors. Los Alamos Scientific Laboratory (LASL) is currently performing these cavity reactor experiments in cooperation with UTRC. Also integrated into this plan is the demonstration of an argon/UF₆ injection, separation, and recirculation system to efficiently separate UF₆ from argon in a form adaptable to subsequent recycling in the uranium plasma experiment. Figure 2 is a schematic of the system for the PCR unit cell configuration. A review of the past work is contained in Ref. 5.

Performance of static UF₆ critical experiments has been accomplished (Ref. 6). Key objectives of the initial static UF₆ and subsequent flowing UF₆ reactor experiments were to facilitate (1) research on gaseous cavity reactor physics and on nonequilibrium optical radiation from fissioning UF₆, (2) demonstration of physical applications of nonequilibrium optical radiation such as direct nuclear pumped lasers, and (3) demonstration of methods for heat extraction for low proliferation risk power generation and propulsion applications.

PCR technology studies at UTRC currently consist of several experiments and theoretical investigations directed toward evaluating the feasibility of the PCR concept. Extensive non-nuclear vortex flow and plasma fluid mechanical research has been conducted over the past fifteen years at UTRC. Past fluid mechanics (nonplasma) experiments (Ref. 7) have indicated that a radial inflow vortex is well-suited for applications which require the preferential containment of a heavy gas within a light gas created by the radial inflow vortex. A radial-inflow vortex flow pattern is characterized by an essentially laminar internal radial stagnation surface across which there is no net inward radial buffer gas flow.

Other previously reported experiments (Ref. 8) have been conducted on the confinement of argon rf plasmas. These tests were directed primarily toward development of a high-intensity, high-power-density plasma energy source (equivalent black-body radiating temperatures >6000 K). Some of these initial exploratory tests included direct injection of very dilute mixtures of UF₆ (typically, 1 percent UF₆ in an argon carrier gas) into the argon rf plasma. Coating of the fused-silica peripheral wall occurred but short-time sustained UF₆ plasma operation was demonstrated. Particle feeder systems were also developed which permitted steady-state injection of carbon (C), tungsten (W), uranium dioxide (UO₂), and uranium oxide (U₃O₈)
into test chambers; operating pressures up to 40 atm were demonstrated. In general, these exploratory test results confirmed that simulated fuels could be confined fluid-mechanically with steep concentration gradients at the edge-of-fuel location.

Reference 9 summarizes the results of initial laboratory-scale experiments in which pure UF₆ was injected into an argon-confined, steady-state, rf-heated plasma to investigate some of the characteristics of plasma core reactors. The overall test results demonstrated applicable flow schemes and associated diagnostic techniques have been developed for the fluid-mechanical confinement and characterization of uranium vapor within the rf plasma.

The performance of high power, flowing UF₆ critical experiments requires development of reliable techniques and equipment for utilizing UF₆ over a wide range of temperatures and pressures. Also required is the associated closed-loop flow system and vortex flow confinement scheme. The results of this technology will ultimately allow operation of an approximately 5 MW self-critical fissioning uranium plasma core reactor. This research report presents results of the continuing uranium plasma confinement tests, together with the associated diagnostics and exhaust systems applicable to plasma core reactors. These tests were conducted using the UTRC 1.2 MW rf induction heater facility with pure UF₆ injected for long time periods into the steady-state, argon-confined, rf-heated plasmas.
DESCRIPTION OF PRINCIPAL EQUIPMENT

UTRC 1.2 MW RF Induction Heater

The experiments reported herein were conducted using the UTRC 1.2 MW rf induction heater system. Refer to Ref. 9 for a detailed description of the rf induction heater system. The rf operating frequency used in the experiments was approximately 5.4 MHz. The rf output power was supplied by two power amplifier tubes which drive a resonant tank circuit (resonator section) of unique design. A photograph of an assembled test configuration installed concentrically within the set of 9-cm-dia water-cooled rf work coils within the resonator section of the rf induction heater is shown in Fig. 3. The entire resonator section consisted of two arrays of ten vacuum capacitors, located (as shown in Fig. 3) within a 1.7-m-dia cylindrical aluminum test tank. Each vacuum capacitor array was connected with a single turn, silver-plated work coil.

The front of the test tank was a removable dome (shown removed in Fig. 3) containing five (10-cm-dia) view windows for observation of the test section. This permitted rapid access to the test section for inspection of uranium compound residue deposition on different test chamber and primary exhaust duct components after completion of a test.

All components of the rf induction heater were water-cooled; measurements were made of all quantities necessary for performing a component and overall system power balance on the rf equipment. An automatic twenty-four channel temperature recorder system was used to monitor all the thermocouples located throughout the rf induction heater system, the components of the rf test chamber, and the various cooling water and gas reference temperatures.

Basic Test Chamber Configuration

Figure 4 is a sketch showing a simplified cross section of the basic test chamber configuration employed in the 1.2 MW rf induction heater tests with pure UF₆ injection. Different test chamber configurations were tested before selecting the configuration and flow scheme which demonstrated the best confinement characteristics. These alternate configurations included (1) endwall injection with dual on-axis thru-flow exhaust and provision for axial bypass, (2) endwall injection with bluff-body stabilization and on-axis thru-flow exhaust, (3) endwall injection with off-axis annular exhaust, (4) peripheral wall injection, and combinations of the above. The configuration selected was based on the test results reported in Ref. 9; several desirable features are incorporated including the ability to independently vary the distribution of exhaust gas flow (axial bypass) and cooling water to the peripheral wall annulus and each endwall assembly. The peripheral wall was
comprised of a concentric set of water-cooled fused-silica tubes. The inner tube was 5.7-cm-ID x 6.1-cm-OD; the outer tube was 6.5-cm-ID x 7.3-cm-OD. The argon vortex was drawn from the right endwall only by a set of eight equally spaced stainless steel injectors located tangent to the periphery of the endwall. The axial distance between endwalls was fixed at 10 cm. A vacuum start technique was employed in all tests. The rf plasma was ignited at approximately 10 mm Hg using breakdown of the argon gas which occurred at a resonator voltage of about 4 kV. This technique had two advantages: (1) it eliminated the introduction of foreign materials into the test chamber; and (2) it permitted a partial purging between tests. As shown in Fig. 4, the UF₆ injector, located on-axis and concentrically within the right endwall, was fabricated from a 50-cm-long three concentric copper tube assembly; the injector tip protruded 2 cm into the test chamber from the face of the endwall. High pressure water (20 atm) heated to approximately 350 K via a steam heat exchanger flowed at 0.14 l/s between the concentric tubes of the UF₆ injector. This provided cooling relative to the hot plasma environment while still maintaining a high enough temperature in the injector to permit flowing the pressurized gaseous UF₆ without solidification in the UF₆ transfer line/injector.

Argon Buffer Gas and UF₆ Supply Systems

Figure 5 is a schematic of the argon buffer gas and UF₆ supply systems. Commercial grade argon gas was supplied to the test chamber, via a filter and gas temperature conditioning system, from a 72.5x10³ l bottle supply. Flow meters were used to measure the argon mass flow rate during the tests. The exhaust gases (argon plus other volatile uranium compounds) were removed from the test chamber through exhaust ducts and, in turn, routed through an appropriate effluent gas collection system. The UF₆ exhaust system is shown in the top portion of Fig. 5. Two, 0.5 l collection vessels immersed in a liquid nitrogen dewar collected the condensible uranium compounds. A vacuum pump system was used for the rf plasma starting sequence and to permit outgassing the components between test series. Flow control valves were used to adjust the pressure in the rf uranium plasma test chamber. The remaining exhaust gases were finally ducted to a neutralizing (NaOH+H₂O) trap located on the roof of the laboratory. The UF₆ supply system is shown in the lower right portion of Fig. 5. This UF₆ handling and feeder system was developed to provide a controlled and steady flow of heated UF₆ at temperatures up to about 450 K. The principal components of the UF₆ transfer system are the UF₆ boiler, the boiler heat supply system, the flow control system, and the UF₆ condenser (exhaust) system. The boiler was a 2 l Monel cylinder rated at 200 atm working pressure. Monel was selected for the cylinder and feed lines because of its resistance to chemical attack by hot, pressurized UF₆. (Refer to APPENDIX A for additional details on the corrosion aspects.) A heat exchanger to provide internal heating was located within the bottom of the boiler. As shown in Fig. 5, electrical resistance heater tape was wrapped around the majority of components. An insulated 3.5 kW electrical heater surrounded the boiler and was used to reach the desired equilibrium temperature and
pressure prior to flowing the UF\textsubscript{6}. A variable powerstat controlled the evaporation rate and temperature within the boiler. In the tests reported herein, use of the electrical heater assembly alone was sufficient to provide the required flow rates. Appropriate safety aspects were incorporated; these included (1) a removable plexiglass enclosure which surrounded the boiler and was connected via a flexible metal duct to the exhaust gas scrubber system located on the laboratory roof, and (2) a high pressure rapid cool-down system (heat exchanger coils) located within the boiler. Dual sets of welded-bellows-type shutoff valves and burst discs routed to the exhaust system were also used for added safety. A linear mass flow meter, calibrated for UF\textsubscript{6}, provided on-line determination of the UF\textsubscript{6} mass flow rate prior to entering the UF\textsubscript{6} injector assembly. By incorporating a Monel transducer, the unit was capable of handling heated UF\textsubscript{6}. The meter basically consisted of an electrically-heated tube and an arrangement of thermocouples to measure the differential cooling caused by the UF\textsubscript{6} gas passing through the tube. The thermoelectric elements generated a dc voltage proportional to the rate of mass flow through the tube. Due to partial coating of the unit throughout the test series, periodic recalibrations and chemical cleaning were required.

Based on the results of exploratory UF\textsubscript{6} handling and flow metering tests and test results reported in Ref. 9, the need for elimination of as much contamination as possible from the UF\textsubscript{6} supply and flow handling system was evident. Refer to Ref. 9 for a detailed discussion of the component preparation, cleaning procedure, and post-analysis used in the UF\textsubscript{6} supply system. The system was designed and tested to mass flow rates up to about 5 g/s and subsequent possible injection of pure JF\textsubscript{6} into the rf plasma test chamber operating at pressures up to approximately 20 atm. For reference, the vapor pressure of UF\textsubscript{6} at room temperature is approximately 130 torr; at 450 K it is about 20 atm. Refer to Ref. 9, APPENDIX C, for additional details on the properties and assay of the as-received JF\textsubscript{6}.

**Test Gas Contaminant Control**

A review of the available literature indicates that the uranium-oxygen and uranium-fluorine systems represent some of the most complex chemical systems known. In addition, some of the published purity data (refer to APPENDIX A) are not in complete agreement between different investigators. In relation to this, many references point out the extreme importance of minimizing the presence of moisture and oxygen in the test system. To aid in reducing these contaminants, a dual trap system (as shown in Fig. 5) was fabricated and installed in a parallel arrangement with the existing argon inlet flow system. A cooled molecular sieve (alkali metal alumino-silicate) was used to trap out the moisture and a heated trap (pure copper filings at 750 K) was used to reduce the O\textsubscript{2} concentration. Prior to transferring the UF\textsubscript{6} into the boiler system, the UF\textsubscript{6} was filtered through a NaF trap (T \geq 450 K) to remove the majority of HF. To provide an indication of the H\textsubscript{2}O levels present, two
independent calibration tests were performed. In one test, a Linberg SB dewpoint instrument was used; in another, a Panametrics Model 2000 in-situ hygrometer instrument was employed. Using the dewpoint instrument, H₂O concentration levels from about 480 to 650 ppm were recorded when no molecular sieve was used. Inclusion of the filter resulted in an approximately 100X decrease in the H₂O content. Comparison of these results with those obtained using the in-situ hygrometer instrument revealed approximately the same trend with some differences in the absolute level. These results emphasized the requirement to adequately filter all the test gases used in the test program.

Diagnostic Equipment

The total power deposited into the uranium rf plasma was obtained from an overall test chamber energy balance by summing the power lost by radiation, power deposited into the annular coolant (including the partial contribution from the radiation attenuating dye) of the peripheral wall, power deposited into the endwall assemblies, power convected out the exhaust ducts, as well as, power deposited into the exhaust heat exchanger and UF₆ injector assembly. The power radiated from the plasma was measured using a specially constructed radiometer and chopper wheel assembly. Refer to Ref. 9 for additional details. Continuous observation of the plasma during the test was accomplished using an overhead projection screen system. Photographs (using neutral density filters) taken through the various viewports were used for estimating the discharge diameter and shape. A tunable cw single-frequency dye laser system was used to provide the very narrow uranium (UI) line at \( \lambda \approx 591.54 \) nm used in the absorption reference calibration tests. Refer to Ref. 9 for a detailed description of the dye laser system and test procedure.

To permit a detailed post-test analysis of the samples of residue collected from the various components of the test chamber and primary exhaust system, the following UTRC instrumentation was employed:

1. Perkin-Elmer IR Spectrophotometer (Model 457) -- permitted identification of compounds using IR spectrophotometric absorption measurements (2.5-40 \( \mu m \) wavelength range) of reference material standard compounds and small samples of residue removed from test chamber and exhaust system components (see Fig. 7 for schematic of IR Spectrophotometer system).

2. Cameca Scanning Electron Microprobe (Model CAMEBA) -- permitted determination of the elements present in the residue samples and also scanning electron micrographs. Showed topographical and compositional variations and permitted x-ray mapping of the individual elements present.

3. Norelco X-Ray Diffractometer (Mark II) -- permitted identification of compounds present in the residue samples by subjecting them to copper Kα radiation and comparing the resulting x-ray diffraction patterns with reference standards.
4. Hitachi Electron Microscope using selected area diffraction (SAD) (Model HU-11) -- permitted identification of compounds present in the residue samples by subjecting them to electron bombardment. It also provided an indication of the relative crystal structure of the material.

5. 3M Ion Scattering Spectrometer (ISS)/Secondary (or sputtered) Ion Mass Spectrometer SIMS (Model 520 B) -- permitted identification of the various elements and compounds present in the residue samples. The unique features of this instrument that distinguish it from the other instruments described above are (a) it was sensitive to just the outer monolayer of the surface, (b) its sensitivity was as high as one part of a monolayer per million, (c) it gave positive identification of the compounds, and (d) if required, it could detect hydrogen and distinguish isotopes of uranium.

Equipment and Systems for Sampling and Analyzing the UF₆ Concentration In the Effluent Gases During the UF₆ RF Plasma Tests

Figure 6 is a schematic showing the basic UF₆ exhaust gas sampling system used in both the IR spectrophotometer absorption and Time-of-Flight (T.O.F.) mass spectrometer measurements. Exploratory tests using both these type systems demonstrated the feasibility of employing either of the two above systems for off- and/or on-line UF₆ effluent gas measurements. The system shown in Fig. 6 illustrates the three different locations used with the sampling probe assembly. The sampling probe was fabricated from a 1.6-mm-OD x 1.5-mm-ID chemically cleaned stainless steel (based on availability and size) tube and located on the centerline axis of the exhaust ducts at the various locations shown in Fig. 6. An appropriate exhaust gas trap, valve assembly, and vacuum pump system was used to permit a continuous flow of sample gas through the sample cell in the case of the IR system and to the T.O.F. inlet head in the case of the mass spectrometer system. The final IR cell was fabricated from Kel-F material; Kel-F was used because it is a relatively nonreactive fluorinated polymer. A pair of AgCl (Silver chloride) windows spaced 10-cm-apart established the active path length. Where required, Kel-F oil was used to provide a seal on the valve/stopcock assembly. For calibration of both systems, a 0.5L Monel supply vessel filled with filtered UF₆ was used. All line lengths were minimized to enhance the response time and the lines were surrounded by electrical heater tapes maintained at approximately 425 K.

Figure 7 is a schematic of the IR spectrometer system used for both the posttest residue analysis and the UF₆ rf plasma exhaust gas analysis. This unit provides a continuous record of the infrared transmittance of a sample (gas, solid, or liquid) as a function of wavelength. In operation, the radiation emitted by the source is divided into two beams. One beam passes through the sample, which absorbs radiation wavenumbers corresponding to its characteristic molecular vibration frequencies, while the other serves as a reference. In the photometer section the two beams are combined by a rotating semicircular sector mirror to form a single beam consisting of alternate pulses of radiation from the sample and reference beams. This combined
beam passes into the monochromator where it is dispersed by a grating into its spectral components. After leaving the monochromator the radiation passes through one of a set of optical filters. Finally, the transmitted radiation is focused onto a thermocouple detector. The remaining components consist of the amplifier, rectifier, modulation and servo motor systems. The recorder is mechanically linked to the attenuator, such that the pen is displaced by an amount proportional to the change in sample transmittance.

Figure 8 is a photograph of the equipment used in the on-line IR spectrophotometer absorption measurements. In these tests a portion of the exhaust stream from the rf plasma test chamber was routed into the Kel-F cell (see Fig. 6). Additional details of the Kel-F cell installed in the IR spectrophotometer sample section are shown in Fig. 9.

Figure 10 is a photograph of the T.O.F. mass spectrometer and associated equipment as used in the initial UF₆ rf plasma tests. As shown, the inlet section was located close to the exhaust duct assembly of the plasma test chamber. An oscilloscope and a strip chart recorder were used for data acquisition. For the initial tests, a 1.6-mm-OD stainless steel hypodermic sampling probe (identical to type used in IR absorption measurements described in prior section) was located downstream of the high pressure heat exchanger assembly shown in Fig. 6 and on the centerline of the on-axis exhaust duct. The interconnecting line (≈70 cm-long) of 6-mm-OD chemically clean copper tubing was surrounded by electrical heater tape and connected to a Nupro stainless steel bellows shut-off valve. See Fig. 6 for a schematic of the plumbing connections and inlet system used in these tests. The line lengths and interconnections were made as short as possible to enhance the response time. Several modifications were made to the equipment including extending the spectral range to mass numbers of approximately 400, and replacing part of the inlet system with corrosion resistant materials. Some general comments on the operation of this particular type of mass spectrometer follow. Figure 11 is a schematic representation of the T.O.F. mass spectrometer. Specifically, in a T.O.F. mass spectrometer, the gas molecules of interest are introduced into the source region and ionized by bombardment with low energy (70-100 ev) electrons, as schematically indicated in Fig. 11. Within this energy range, the molecules are usually singly ionized. In the ionization process, in addition to the removal of an electron from the molecule, rupturing of molecular bonds can also occur. This bond rupture is normally called molecular fragmentation. The ionized molecules are then pulsed out of the source region by an electric field and enter a field free region — the analyzer. The ion source is designed so that most ions, regardless of their mass, acquire approximately the same energy. Because the drift region is field free, the ions simply coast with the lighter ions traveling faster than the heavier ones. These differences in velocity result in the arrival of isobaric (equal mass) packets of ions at the detector at different times. The detector is an electron multiplier whose first stage converts the ion packets into electron packets. The electron packets are amplified and fed into a readout or data processing unit (see bottom of
Fig. 11 for example of instrumentation output). Since these processes must take place without significant intermolecular collisions, a vacuum system is used to reduce the gas concentration around the analyzer to a level ($\approx 10^{-5}$ torr) where particle mean-free paths are long. The currents measured by the electrometer amplifier and the peak heights observed on the oscilloscope are linearly related to ion abundance and, hence, species concentration. Proper calibration of the instrument can therefore lead to reproducible quantitative measurements.

**Details of UF$_6$ RF Plasma Test Chamber Interstage Exhaust Duct**

Figure 12 is a sketch showing a cross section of the test chamber and primary interstage exhaust duct. This exhaust duct system is referred to as the interstage exhaust duct since it interfaces the test chamber with the secondary exhaust duct assembly. The test chamber endwalls incorporated provisions for locating thermocouples both within the endwall and on the surface of the endwall face exposed to the uranium rf plasma. One thermocouple tip was located flush (exposed to the UF$_6$ plasma region) with the face of the endwall surface at a radial distance of 1.8 cm from the on-axis centerline; the other thermocouple was located at the same radial distance from the on-axis centerline (different azimuthal location) but was recessed into a well with the tip of the thermocouple 1 mm behind the face of the endwall. The exposed thermocouple was specially constructed using a nickel sheath to better protect it from the hostile uranium plasma environment within the test chamber. (Refer to APPENDIX A for additional discussion on UF$_6$/F$_2$ corrosion effects and materials compatibility.) The endwall assemblies were also constructed and manifolded so that independent and variable cooling water flow rates could be applied to each unit as required to minimize the wall coating due to uranium compound deposition. An alternate left (exhaust side) endwall assembly was also fabricated such that a tungsten/tungsten-rhenium (W/WRh) thermocouple could be located within the on-axis thru-flow duct at the axial midplane location of the endwall assembly.

To allow estimates of the type and quantity of uranium compound residue that may deposit on the inside surface of the primary exhaust duct located immediately downstream of the left endwall assembly, a 16-mm-ID water-cooled stainless steel (304) interstage exhaust duct assembly was used. Attachment flanges were welded to each end of the 13-cm-long assembly to simplify removal of the interstage exhaust duct for post-test inspection after uranium rf plasma tests with pure UF$_6$ injection. The test configuration used in earlier tests (Ref. 9) employed a nonremovable 8-mm-ID water-cooled copper tube exhaust duct assembly that was silver soldered directly to the endwall assembly; this precluded removing the exhaust duct assembly for inspection and material residue analysis after the tests.
Provision was also made for locating a W/WRh thermocouple within the attached flange at the exit plane of the interstage exhaust duct. By using a swage/lucking type of fitting, the tip of the thermocouple could be located flush with the inside diameter of the exhaust duct or radially indexed to the axial centerline position. As can be seen in Fig. 3, electronic ice-path compensators were used with rf-shielding and radiation insulation material surrounding the thermocouple shields, plug-ins, and leads; this helped in providing an interference-free output signal during the uranium rf plasma tests. The output from all the individual thermocouples was recorded on strip chart recorders. The UF₆ injection endwall assembly, not shown in Fig. 12, was identical to the exhaust endwall assembly except for the replacement of the axial bypass exhaust section with the argon buffer gas vortex injectors and resizing of the on-axis duct for housing the UF₆ injector assembly (see Fig. 4). The easily removable interstage exhaust duct assembly shown in Fig. 12 could also accommodate several different types of diluent gas injectors (e.g., coaxial, radial injection, and swirl) at the upstream end. These exhaust flow schemes permitted injection of a diluent gas into the peripheral region of the interstage exhaust duct as a means of reducing the uranium compound wall coating. The assemblies also have provision for including either thermocouples or exhaust gas sampling probes at the inlet and exit plane locations. Figure 13 is a photograph of the three different diluent gas injectors used at the inlet of the interstage exhaust duct. Figure 14 is a photograph which shows the entire test chamber configuration and interstage exhaust duct/diluent gas injector assembly as used in the UF₆ rf plasma tests.

Figure 15 is a sketch of the cross section of the transpiration injection interstage exhaust duct assembly. This assembly also has provision for including either thermocouples or exhaust gas sampling probes at the inlet and exit plane locations. The dual concentric wall arrangement consists of a 16-mm-ID, 5-mm nominal bore size Monel duct (1.5-mm-wall thickness) located concentrically within a solid tube outer housing. The annular region acts as the diluent gas injection manifold. The unique feature of employing a porous wall scheme is that, in addition to reducing the bulk temperature of the stream and balancing some of the radially outward diffusion and centrifuging of the uranium compounds with the radial inward injected bleed gas, fluorine gas may be added to the bleed carrier gas to aid in regenerating the various gaseous uranium compounds back to UF₆. Figure 16 contains photographs illustrating additional details of the porous wall duct assembly. The bottom of Fig. 16 shows several of the different porosity ducts used in some of the exploratory flow visualization tests. These consisted of bench-scale tests using a mock-up assembly of the porous Monel duct scheme.

Figure 17 is a photograph showing the porous Monel interstage exhaust duct assembly connected to the downstream end of the primary interstage exhaust duct assembly as used in the UF₆ rf plasma exhaust gas tests.
DISCUSSION OF TEST RESULTS

In preparation for future interfacing of the UF₆ rf plasma experiments reported herein and near-term hot argon/UF₆ exhaust separator, recovery, and regeneration schemes, emphasis was placed on the development of techniques for minimizing the deposition of uranium and uranium compounds on the test chamber peripheral walls, endwall assemblies, and primary exhaust ducts. Figure 18 is a schematic illustrating (by letter code) the key components examined in the post-test analysis. Also shown for reference are the various possible inlet contaminants and species present within the plasma test chamber prior to entering the primary exhaust duct system. Concurrent with the requirement to minimize the uranium compound exhaust deposition is the requirement to maximize the ratio of UF₆ to UF₆ decomposition products in the effluent exhaust gas. To aid in this, different diagnostic techniques have been investigated, including both off- and on-line types, to determine the feasibility of monitoring the concentration of UF₆ and other primary and secondary (contaminants) exhaust gas constituents.

Post-Test Residue Deposition As a Function of Endwall And Interstage Exhaust Duct Operating Characteristics

To aid in estimating the effect of reducing the cooling to the endwall assemblies and interstage exhaust duct assembly on residue deposition, a series of exploratory tests were conducted using the test configuration and exhaust duct system shown in Fig. 12. See also Fig. 14 for a photograph of the assembled configuration within the 1.2 MW rf induction heater test tank.

Initial tests conducted with the uranium rf plasma operating in the 15 to 45 kW total power level range, a chamber pressure of about 2 atm, and mass flow rates of UF₆ from about 0.005 to 0.03 g/s, indicated the temperatures measured within the endwalls (recessed thermocouple location) ranged from approximately 320 K to 500 K. The corresponding temperatures at the tip of the thermocouple located flush with the face of the endwall ranged from approximately 375 K to 760 K. In these tests the argon buffer gas flow rate was maintained constant at 2.7 g/s; the rf operating frequency was 5.4328 MHz, and the annular axial bypass flow rate was preset at approximately 0.6 g/s (i.e., 22 percent of the main argon buffer gas flow rate). In these tests, the UF₆ transfer system, flow metering equipment, and exhaust duct/trap system shown in Fig. 5 were used. Also, throughout this entire test series, the on-line dye laser (uranium line λ = 591.54 nm) absorption system (see Fig. 13 of Ref. 9) was employed in selected tests to establish the reference operating conditions of the uranium rf plasma compared to prior test results (Ref. 9).
The cooling provided to each of the components was as follows:

- **Annular cooling water flow rate** - 0.75 L/s;
- **Right endwall cooling flow rate** - 0.095 L/s;
- **Left endwall cooling flow rate** - 0.085 L/s; and,
- **Interstage exhaust duct cooling flow rate** - 0.38 L/s

These initial test results indicated that to aid in eliminating some of the post-test residue coating, the surfaces of the endwalls and exhaust duct systems would have to be operated at elevated temperatures. After completion of these tests, a post-test material analysis examination was performed to determine the type of residue coating deposited on each component. Some of the diagnostic equipment described in the 'Description of Principal Equipment' section was used in this analysis. The results indicated the surface of the UF₆ injector and the region of the UF₆ injection endwall assembly immediately surrounding the injector (to a distance of about midradius) exhibited a light coating of UO₂F₂, UF₄, and UO₂ (typically hundreds of milligrams). Figure 19 is a photograph of the rf plasma test section after a representative variable surface temperature endwall test. The post-test uranium compound coatings on the UF₆ injector and both endwall faces can be clearly seen in the photograph. The face of the left endwall assembly also displayed a light coating of primarily UO₂F₂ and UF₄ (typically 50 to 100 mgs) that also extended out to approximately midradius. Examination of the inner wall of the removable interstage exhaust duct and the endwall on-axis thru-flow duct also revealed a coating of pale green material (typically hundreds of milligrams).

To establish that the residue was indeed a coating and not a plating, part of the sample material removed was analyzed by separate emission spectroscopy. The results indicated the principal elements to be almost totally uranium, fluorine and oxygen with no significant traces of reactant wall material; a coating can be more easily removed from the wall as compared to a plating that might occur from the reaction between hot uranium compounds in the vapor state and the wall surface material.

Analysis by IR spectrophotometry revealed the residue to consist primarily of UO₂F₂ (note that UF₄ does not display a characteristic IR spectrum); analysis by electron diffraction also indicated the presence of UF₄, UO₂, and an additional amorphous material not identifiable by either the electron diffraction or IR spectrophotometer analysis techniques. In these initial tests, the thermocouples indicated temperature profiles within the interstage exhaust duct at the downstream station ranged from approximately 300 K at the wall to about 2000 K at the centerline for the lower power conditions. The W/WRh thermocouple located at the upstream station and ½ of the distance from the centerline to the wall indicated temperatures up to about 2700 K prior to its immediate failure due to chemical attack. (See Fig. 20 for an example of the type of temperature profiles measured.) Other measurements taken at off-axis locations and used for extrapolation to the centerline, indicated centerline temperatures exceeding 4000 K occurred. Post-test examination of the tip of the W/WRh thermocouples under a high power microscope confirmed the fact that the molybdenum sheath (melting point \( \approx 2900 \) K) had reacted with the hot uranium/fluorine compounds in the exhaust duct.
Part of the overall objective of this research effort was to gather information relative to the corrosive/erosive effects of hot, pressurized UF₆ and its various decomposition/reactant products (including F₂ and HF). Available information on the corrosion aspects of different materials exposed to UF₆ was presented in Ref. 9. The majority of the information relates to the rate of corrosion (µm/hr) of different materials exposed to UF₆ at a pressure of only 0.32 atm, and temperatures of about 1000 K. Over four orders of magnitude range in corrosion rate have been reported for the various materials tested (typically, 10⁻² to 10² µm/hr). These include Monel, nickel, inconel, gold, platinum, and stainless steel.

In future tests, the requirement for additional equipment being located downstream of the uranium rf plasma test chamber (e.g., exhaust gas UF₆ separator, recovery, and conditioning components) together with the need for thermocouples and other exhaust gas sampling probe devices to be located in the exhaust ducts and operated for sustained times necessitates further exploration into the corrosive aspects of the hot, pressurized UF₆ exhaust. As an example, an initial review of the literature indicates no thermocouple sheath materials are readily available that can withstand long-time, high-temperature, high pressure exposure to UF₆/fluorine. Additional information is provided in APPENDIX A.

Another important aspect of the research being conducted is in the area of contamination. Contamination in all components must be considered: the UF₆ supply itself; the UF₆ feeder and transfer system; the test chamber (e.g., minute leaks of H₂O); the argon buffer gas supply; the various components of the exhaust system; the various joints, seals, and O-ring materials; and, the handling procedures in the post-test analysis. APPENDIX A includes some additional information related to contamination. As a specific example, the elimination of all potential sources of moisture (H₂O) and/or air (O₂) is most important in this type of test series, since even small concentrations can result in several unwanted chemical reactions which can effect the quantity and type of residue deposited on the walls of the exhaust duct components and/or composition of the effluent gas. An example of such a reaction is:

\[
\text{UF}_6 + \text{SiO}_2 \xrightarrow{\text{catalyst}} \text{SiF}_4 + \text{UO}_2\text{F}_2
\]

In this case, the source of the SiO₂ is the inner fused-silica peripheral wall of test chamber.

Test results indicated a molecular sieve and oxygen trap system, of the type shown in Fig. 5, was required in the inlet argon buffer gas supply system to significantly reduce the contamination level. The effectiveness of the filter/trap system was verified in the following set of tests. A parallel connection arrangement was used such that the argon inlet filter/trap system could be activated only when desired. The configuration used in these tests is shown in Fig. 5. The discharge was operated at a power level of approximately 45 kW, a chamber pressure level of 1.75 atm, and
an argon buffer gas flow rate of 3.04 g/s. For this series of tests, these operating conditions were maintained constant to permit a direct comparison of the argon buffer gas inlet system operating both with and without the filter/trap system. The test results are shown in Fig. 21. At aUF\textsubscript{6} mass flow rate of 1.8x10^{-2} g/s, an axial bypass flow of 0.57 g/s, and test times of approximately three minutes, typically 600 to 750 mg of residue coating was deposited on the inner wall of the removable interstage exhaust duct assembly. In these tests, the cooling water injection flow rate to the interstage exhaust duct assembly was maintained constant at 0.38 l/s. Two additional tests at approximately the same test conditions resulted in a reproducibility of the deposited residue within 10 percent (refer to upper right portion of Fig. 21). When both the molecular sieve and oxygen trap system were activated, a factor of approximately 2.5X reduction in the total quantity of residue deposited on the inside surface of the exhaust duct occurred. During these tests, measurements were also made of the quantity of residue deposited on the faces of both endwall assemblies and the UF\textsubscript{6} injector (refer to data key of Fig. 21). In the tests not employing the filter trap system, up to about 10 mg was deposited on the exhaust endwall, up to about 20 mg on the face of the injection (argon inlet) endwall, and up to 40 mg on the UF\textsubscript{6} injector assembly that protruded 2 cm into the test section. When the argon inlet trap systems were used, an approximate factor of 2X reduction in the quantity of material deposited on these components was measured. These results confirm the fact that using traps on the inlet gas system help to reduce the quantity of residue deposited on the surfaces of the test chamber.

A series of tests was also conducted to permit an estimation of the degree of wall coating as a function of the water-cooling flow rate applied to the interstage exhaust duct assembly. These corresponded to a fixed test time of three minutes (total UF\textsubscript{6} mass flow of 3240 mg); all other conditions were maintained approximately constant. The results are illustrated in Fig. 21. The high-pressure cooling water flow rate applied to the interstage exhaust duct was throttled down in discrete steps from the maximum of 0.38 l/s to approximately 0.088 l/s (85 percent reduction). This was the lowest level determined by heat transfer calculations to be safe for the steady-state operation without possible component failure. At this condition, approximately 25 mg of residue was deposited (relatively uniformly) onto the interstage exhaust duct.

In one test, the cooling water flow rate was reduced still further; this led to a weep-type water leak at the welded junction between the inner and outer concentric tube assemblies of the interstage exhaust duct. This leak was discovered during rf plasma vacuum start procedure; it also showed up at a water pressure check at 30 atm. This temperature induced failure served as an example of the importance of verifying that all sources and traces of contamination and/or impurities are reduced to the lowest possible levels prior to conducting a given test series; if not, questionable data interpretation may occur which would not be representative of the selected test parameters used.
The results obtained indicate the desirability to operate the endwall assemblies and the interstage exhaust duct assemblies at as high a temperature as possible compatible with the structural material limitations.

Tests With Variable Flow Exhaust Duct Interstage Assemblies

Figure 12 shows the configuration used in the tests with the removable, water-cooled interstage exhaust duct assembly which could incorporate different types of exhaust flow augmentation schemes (i.e., coaxial injector, radial injector, and swirl injector). Figure 13 is a photograph showing details of the different design diluent gas injector assemblies. Each assembly had an inside diameter of 1.6 cm; the thickness of the radial injector unit was 0.6 cm, the other two units were 0.95 cm in thickness. The injection cross-sectional area of each component was selected based on flow calculations and estimates of the hot flow test conditions inside the exhaust duct inlet. Five equally-spaced 1-mm-dia orifices were employed in the radial injector scheme, one annular injector ring (annular slot height 1.6 mm) in the coaxial injector scheme, and four equally-spaced tangential injectors (1.2-mm-ID) in the swirl injector scheme (see Fig. 13).

Figure 14 is a photograph showing the entire test configuration installed in the 1.2 MW rf induction heater test tank. In this particular photograph, the coaxial injector scheme was installed and the photograph was taken immediately following one of the uranium rf plasma tests. Visible in the photograph is a light coating of residue material on the UF6 injector assembly and a very light coating on the inner radius section of the left endwall assembly. An example of the test results is shown in Fig. 22. The weight of residue deposited on the ID of the interstage exhaust duct assembly is shown versus the argon flow rate through the particular diluent injector assembly used. The range of test conditions are shown in the figure along with the corresponding key to the type of injector assembly used. To provide a reference base for the no argon diluent flow case in addition to a reproducibility check, several data points are shown in the upper left corner of Fig. 22. The reproducibility was approximately ±15 percent. Bearing in mind the entire test chamber and exhaust duct system were disassembled and cleaned after each hot flow test, this type of reproducibility was considered good. As can be seen in Fig. 22, the introduction of as little as 0.14 g/s of argon diluent resulted in an approximate order of magnitude reduction in wall coating on the interstage exhaust duct. Further increases in the argon diluent flow rate did not have as pronounced an effect on continuing to reduce the wall coating; thus, changing exhaust conditions may be the dominant effect on the coating level.

At argon diluent injection flow rates of >0.6 g/s, some oscillations were noted in the uranium rf plasma discharge. Apparently, as the flow rate of the diluent gas approached about one-third of the total mass flow rate (without injection) the exhaust conditions were changed sufficiently to result in upstream perturbations on the discharge. These test results show that within the range of
test conditions used, the use of either a swirl or coaxial type diluent gas injector reduces the residue coating on the inside surface of the interstage exhaust duct. Therefore, this or a similar type of exhaust system flow scheme or a combination thereof may be employed in the near-term interfacing tests of the uranium rf plasma system with an argon/UF₆ separation and recovery system.

Tests With Diluent Gas Injection Porous Exhaust Duct Assembly

An alternate scheme investigated to further reduce the uranium compound residue coatings on the inside wall of the interstage exhaust duct assembly was to use a porous duct (i.e., transpiration injection flow system). The basic configuration is shown in Fig. 15. APPENDIX B contains supporting calculations and an analysis of swirling hot flow within a porous duct with radial transpiration injection. Extensive studies have been published on the heat and mass transfer aspects of hot vortex flow within tubes but little, if any, have been published for the case of a plasma vortex flow within a duct with transpiration injection. The unique feature of employing a porous duct assembly as part of the exhaust duct system is that, in addition to providing the required bulk gas cooling and aid in reducing the uranium compound wall coating, different concentrations of F₂ could be doped into an argon carrier gas, for example, to assist in the possible conversion of some of the UF₆ decomposition products back to UF₆.

Bench-scale exploratory cold flow tests were conducted using a mock-up assembly of the porous duct scheme shown in Fig. 15. Figure 16 is a photograph showing several of the different size porosity ducts tested. The custom fabrication of sintered Monel (desirable from the standpoint of corrosion resistance to hot, pressurized UF₆) tubing in a variety of relatively uniform and small pore sizes, permitted conducting a series of comparison tests. TABLE I lists the metallurgical composition and basic property data of the Monel 400 material used. Mock-up assemblies of porous ducts with nominal pore sizes ranging from 40 μm down to 5 μm were tested using flow visualization techniques. Gaseous hydrogen chloride and ammonia were used as the two reactant gases, with a dense smoke occurring from the reaction. Based on visual observations, the 5 μm nominal pore size Monel tube resulted in a very uniform central core of gases flowing within the duct and confined away from the inside diameter of the tube. The exact confinement core sizes were dependent upon the flow conditions selected, and were representative of those anticipated in hot flow tests. Based on these test results, several removable porous Monel (5 μm nominal pore size) interstage exhaust duct assemblies were fabricated for hot flow testing. The top portion of Fig. 16 is a photograph illustrating their construction. The materials and fabrication techniques (including electron-beam welding) were chosen based on compatibility under the expected operating environment.

However, the exact determination of the axial and radial temperature distributions present in the uranium plasma exhaust duct assembly is difficult and is further complicated by the presence of the vortex flow in the exhaust duct assembly. The latter effect alone can significantly increase the heat transfer coefficient at the surface of the Monel duct.
During the initial hot flow tests (argon only) conducted using the basic configuration shown in Fig. 15, a hairline circumferential crack developed in the inner Monel tube (approximately 1/5 of the way down the duct from the inlet location). This was apparently caused by thermal stress (tensile) in the inner Monel tube assembly. Partial redesign (free floating end scheme) followed by a different welding procedure, appeared to alleviate this problem. However, several follow-on tests later, a similar circumferential crack again developed near the inlet section. Based on the porous duct analysis results reported in APPENDIX B, and the interstage exhaust duct test results reported in the prior section, it was decided to relocate the porous duct exhaust assembly immediately downstream of the interstage exhaust duct. This new test geometry is shown in the photograph of Fig. 17. As can be seen in Fig. 17, surrounding the porous duct assembly, water-cooled coils were silver soldered directly to the outer wall to alleviate the high heat loads, particularly near the end flange locations. This was also required to provide additional protection for the O-ring seals used at the junction of the different flange assemblies.

A series of tests were conducted using this test configuration to determine if the porous Monel duct assembly performed as well as anticipated. The results are shown in Fig. 23. In this figure, the total weight of residue collected from the porous Monel duct is shown versus the test time in minutes. TABLE II is a summary, including the corresponding test conditions, of the data shown in Fig. 23. After completion of the first test, it became obvious that only very small amounts of residue were being deposited on the inside surface of the porous Monel duct. This emphasized the importance for careful removal of the residue for weighing on a balance that was capable of accurate measurements down to micrograms. In these tests, laboratory distilled and deionized water was used to wash off the coatings from the porous duct assembly. After filtering and drying, the residue weight was determined. In selected tests, post-test analysis was conducted using the various diagnostic instruments discussed in the 'Description of Principal Equipment' section. Using the configuration shown in Fig. 15, W/WRh thermocouples were used to provide an estimate of the temperature within the porous duct exhaust assembly (centerline location) during an actual hot flow test. For typical operating conditions corresponding to the tests shown in Fig. 23, the centerline temperature was approximately 1800 K at the downstream location. Near the wall the temperature was approximately 850 K.

Note that as shown in Fig. 23, the test case corresponding to a low UF₆ injection resulted in the lowest residue coating on the wall of the porous duct (72 µg). Alternately, a reduction in the argon diluent gas injection flow rate through the porous duct resulted in a noticeable increase in the post-test wall residue. An indication of the effectiveness of the porous duct for longer test times at approximately the same test conditions is illustrated by the square data points in Fig. 23. An increase in the weight of post-test residue (within the experimental error) is noted as the test time was increased from 2.5 minutes to over eleven minutes. The approximately 150 µg of coating determined was virtually
nondetectible by visual observation. Figure 17 is a photograph illustrating the type of coatings that occurred in the UF6 rf plasma tests with the porous Monel duct (Test Case I, TABLE II). The left endwall had less than 1 mg of coating, the UF6 injector and right endwall assemblies had less than 10 and 3 mg, respectively. The fused-silica peripheral wall had less than 4 mg (a slight whitish coating is observable in Fig. 17 adjacent to the left O-ring assembly) and the porous Monel duct assembly had \( \approx 0.23 \) mg. Based on these results, it appears that use of a porous Monel duct assembly acting as part of the interstage exhaust duct between the uranium rf plasma test chamber and future Ar/UF6 separation and recovery systems will permit transport of the majority of hot UF6 and UF6 composition products out the exhaust duct to a region where they can be efficiently recovered and reprocessed.

Exhaust Gas Sampling Tests Using Off- and On-Line IR Absorption Techniques

A series of exploratory tests were first conducted to provide an initial estimate of the detectibility and type of gaseous constituents present in the effluent flow within the exhaust duct during the actual uranium rf plasma tests. This information is required at different axial locations within the on-axis exhaust duct as well as within the off-axis axial bypass exhaust duct system pending future integration with a hot Ar/UF6 separator and reclamation system.

A review of the literature indicated useful information was available on the infrared (IR) spectra of UF6 between 2 to 40 \( \mu \text{m} \) (Ref. 10). In all cases reported, considerable effort was required regarding purity to obtain consistent test results. For example, the exposure to fused-silica was minimized (note that the peripheral walls of the test chamber used in this test series are high grade fused-silica) and only those results with little or no traces of SiF4 were documented in the literature. The SiF4 results from the reaction between UF6, fused-silica (SiO2), and traces of moisture. Small amounts of HF are always present and extremely difficult to eliminate completely.

Figure 24 shows the infrared absorption spectrum of room temperature UF6 over a wavelength range from about 1200 to 500 cm\(^{-1}\) (8.5 to 20 \( \mu \text{m} \)) as reported in Ref. 10. The reported path length was 10 cm. Note the very intense band at about 623 cm\(^{-1}\) and the moderately strong band (\( \approx 2 \) orders of magnitude less) at about 676 cm\(^{-1}\).

A stainless steel hypo tube (304 type) sampling probe (1.6-mm-OD) was used in these exhaust duct system tests. By using an appropriate exhaust gas trap, valve assembly, and vacuum pump system (see Fig. 6) a continuous flow of sample effluent gas could be drawn through a small (approximately 50 cm\(^3\) volume) sample test cell. The initial cell was fabricated from fused silica (2.5-cm-ID cylinder) and had an active path length of 10 cm between a pair of AgCl windows. A pair of fused-silica stopcocks with Kel-F oil were also installed on the peripheral wall of the sample
cell to isolate the collected sample in preparation for off-line analysis using the IR spectrophotometer. Considerable calibration testing was required before proceeding with an actual hot flow uranium rf plasma test. Two Monel 0.54l canisters containing filtered (using NaF traps) UF$_6$ (approximately 10 gms net) obtained from the main UF$_6$ supply vessel were prepared as standard sources. Electrical heater tapes were wrapped around all the connection lines and valves to maintain temperatures sufficient to eliminate possible UF$_6$ condensation and solidification in the transfer lines. Figure 25a is an example of the IR absorption trace obtained for the evacuated (No UF$_6$ -- 10 $\mu$m) fused-silica sample cell with AgCl windows. In all cases, the path length was 10 cm; a Perkin Elmer Model 457 IR spectrophotometer was used for making the IR absorption measurements. Figure 7 is a schematic diagram of the basic components of the spectrophotometer. The presence of H$_2$O (moisture) and CO$_2$ (carbon dioxide) in the reference beam were detectible at the corresponding wavelengths shown at the bottom of Fig. 25a. A trace of a hydrocarbon impurity at about 3.5 $\mu$m was also evident. The AgCl window transmission cutoff was at approximately 20 $\mu$m as shown at the right side of Fig. 25a. Figure 25b shows the corresponding IR absorption spectrum obtained when the fused-silica cell was filled with approximately 0.5 gm of filtered UF$_6$ and maintained at room temperature. Considerable care was taken in cleaning and thoroughly outgassing and baking the vessel prior to filling. The labels at the bottom of Fig. 25 indicate the trace impurities occurring at the corresponding wavelength. The distinct absorption peaks corresponding to both UF$_6$ and SiF$_4$ are shown by the vertical arrows at the bottom of Fig. 25b. Recall, the SiF$_4$ is attributed to the reaction between UF$_6$, fused-silica, and a trace of moisture. Based on results reported in the literature indicating the critical requirement of eliminating all traces of SiF$_4$, it was decided to fabricate a new test cell out of Kel-F material. This material is a fluorinated polymer that is relatively nonreactive with UF$_6$ and associated fluorine compounds at near room temperature. Unfortunately, it has a melting point of approximately 450 K, therefore care must be exercised with its use in moderate temperature environments. Additional follow-on tests were conducted with the Kel-F sample cell replacing the fused-silica cell. A special fixture was fabricated to permit centrally attaching the AgCl windows, using Kel-F wax to the ends of the Kel-F cylinder. Figure 9 is a photograph showing the Kel-F cell, filters, valves, and AgCl windows installed in the test section of the IR spectrophotometer. The use of the Kel-F cell eliminated the SiF$_4$ contamination found in the earlier tests and consistent calibration data were obtained (similar to that shown in Fig. 24). Subsequently, a series of tests were conducted using the test configuration shown in Fig. 6.

A 20-cm-length of chemically-cleaned 6.4-mm-dia copper tubing wrapped with electrical heater tape connected the sampling probe to the Kel-F sample collection cell. The sampling probe was fabricated with a 90 deg bend near the end to permit a direct flow of effluent gas into the probe. By carefully controlling the valve sequence using the system shown in Fig. 6, several samples of the effluent exhaust gas were collected from actual hot flow uranium rf plasma tests. The three exhaust gas sample probe locations indicated in Fig. 6 were used. In all cases, the tip of the sampling probe was located on the centerline axis of the particular exhaust
duct being investigated. Operating conditions used were similar to those shown in Fig. 21. The sole exception was that the chamber pressure was reduced to approximately 1.2 atm to eliminate the possibility of over pressure damage to the AgCl window seal. Figure 25c illustrates the type of off-line IR absorption spectrum obtained. Note the positive identification of the UF$_6$ peaks (623 cm$^{-1}$ and 676 cm$^{-1}$) when compared to those shown in Fig. 24. The time interval from actual sample collection to start of sample analysis in the chemistry laboratory using the IR spectrophotometer varied somewhat, but was normally about ten minutes. The results shown in Fig. 25c were obtained with the sampling probe located in the upstream position of the on-axis thru-flow duct, as shown in Fig. 6. Similar results were observed for the downstream location but of a slightly reduced magnitude. A series of calibration tests were also completed to verify the negligible effect of varying the test cell temperature and pressure on the IR absorption spectrum of UF$_6$. The test range included cell pressures between 125-300 Torr and cell temperatures between about 300 K - 400 K. When the sampling probe was located in the annular axial bypass exhaust duct, no trace of UF$_6$ was detected in any of the tests. This is of particular importance, since it provides a quantitative measure of the uranium confinement characteristics of the vortex flow employed in the UF$_6$ rf plasma test chamber. Additional tests using off-line wet chemical analysis techniques (total uranium analysis) substantiated the findings of the IR spectrophotometric analysis. The elimination of all the SiF$_4$ absorption bands indicated the choice of Kel-F material combined with careful removal of major contaminants was adequate in providing a good reproducible spectrum. These results indicated the feasibility of using IR spectrophotometric measurement techniques for estimating the UF$_6$ concentration in the exhaust gas system.

To extend this technique to include on-line determination of the gaseous UF$_6$ concentration in the effluent gas, the Perkin-Elmer Model 450 IR spectrophotometer was adapted onto the exit duct/sampling probe assembly of the uranium rf plasma test configuration. Figure 8 is a photograph illustrating this particular on-line test configuration. The major advantages of employing an on-line diagnostic scheme such as this are: a large amount of valuable data can be acquired in a relatively short time span; and, the elimination of possible nonrepresentative sample acquisition due to the occurrence of post-test chemical reactions within the sample cell. Location of the relatively large IR spectrophotometer instrumentation adjacent to the exhaust duct assemblies of the 1.2 MW rf induction heater test tank required considerable rearrangement of equipment. Also a number of preliminary calibration tests were required to verify adequate shielding of the instrumentation from the plasma radiation and stray rf fields. The valving and line interconnections were similar to those shown in Fig. 6 but, due to physical constraints, a longer (≈50 cm) 6.4-mm-dia copper line connecting the sampling probe assembly to the valve on the Kel-F sample cell was required. Electrical resistance heater tape (≈25 K) surrounded the connecting line to reduce the possibility of constitutive deposition on the walls from the effluent gas. This configuration permitted a continuous flow of sample effluent gas through the 50 cm$^3$ volume Kel-F cell while making the on-line IR absorption measurements. Tests were conducted using both the
623 cm\(^{-1}\) and the 676 cm\(^{-1}\) wavelengths since these wavelengths possessed the strongest UF\(_6\) absorbance in the IR range investigated. Figure 26 is an example of the output absorbance signal obtained for the 623 cm\(^{-1}\) wavenumber. In these tests, the x-axis normal wavelength output of the recorder was converted to a linear time scale and the IR spectrophotometer was locked onto the 623 cm\(^{-1}\) wavenumber (determined from prior calibration measurements). The first portion of the trace shows the evacuated Kel-F cell condition (\(\approx 10 \mu m\), which is followed by an argon only (cold flow -- no rf plasma) test condition. The next sequence illustrates a typical reference operating condition with the argon rf plasma only (no UF\(_6\) injection). Some additional signal noise was expected and is noticeable under the rf hot flow test condition. During the next sequence, increasing quantities of UF\(_6\) were injected into the rf plasma in three steps and maintained constant for a sufficient time (typically 30 s) to allow the output absorbance signal to level off. (Refer to TABLE III for additional details.) Immediately following this, the UF\(_6\) injector valve was closed and the rf plasma was manually extinguished. As noted in Fig. 26, the post-test vacuum condition agreed reasonably well with the pretest vacuum calibration; however, a slight realignment of the Kel-F cell was required to bring the signal back to near its original level. Careful post-test inspection of the AgCl window revealed a minute trace of coating which also may have accounted for the inability to achieve the exact pretest calibration level. The data shown in TABLE III illustrate the approximate concentrations measured and confirm the feasibility of using an on-line IR absorption technique for establishing the quantity of UF\(_6\) present in the effluent exhaust gas. The definite advantages of such a system are (1) the ability to collect and analyze a considerable amount of data in a short time (this is particularly important in an experiment such as this wherein several complicated systems must all simultaneously perform correctly (i.e., UF\(_6\) transfer system, 1.2 MW rf induction heater system, single-frequency narrow band dye laser system, and all associated electronic monitoring equipment)), and (2) the potential for eliminating post-test chemical reactions within the sample cell. The experience gained using this system also revealed several potential disadvantages if used in a near-term 1.2 MW rf uranium plasma/UF\(_6\)/argon separator system application: (1) the measurements are primarily limited to UF\(_6\) only; (2) there are cell optical alignment problems and associated AgCl window degradation due to coating and attack by UF\(_6\)/UF\(_6\) decomposition products; (3) there are installation problems related to the physical size of the IR cell and required close proximity of the associated equipment; (4) measurements obtained are weighted-averages and do not provide a true radial concentration profile; and, (5) the limited pressure and temperature range associated with use of the Kel-F cell. Because of these potential disadvantages, an alternate technique was investigated and the results reported in the following section.
Exhaust Gas Sampling Tests Using Off- and On-Line Mass Spectrometer Techniques

In preparation for near-term interfacing of a hot argon/UF₆ separator system with the 1.2 MW rf uranium plasma test facility, a second exhaust gas analysis technique was investigated. This technique involved use of a Time-of-Flight (T.O.F.) mass spectrometer. Review of its capabilities indicated the instrument can be adapted for high resolution, rapid scanning over a wide spectral range (mass numbers), and also possesses the flexibility to analyze both major and minor constituents (e.g., minor contaminants in the UF₆/argon system). This is a unique and important feature not possible with the IR spectrophotometer system discussed in the prior section. The instrument selected was a modified Bendix commercial MA-1 unit. In its standard form the instrument is capable of quantitative analysis of samples as small as 10⁻¹⁵ moles in as short a time as 20 s. Refer to Figs. 10 and 11 and "Description of Principal Equipment" section for additional discussion.

Special applications such as this are possible because the T.O.F. uses a straight-line trajectory for all the ions, employs a planar grid ion source, and collects all the ion masses on each cycle of the instrument by the magnetic electron multiplier detector. Thus, by means of an oscilloscope, every mass peak may be monitored at an interval of 100 μs. Using an appropriate strip chart recorder, the analog output system provides permanent recordings of the mass spectra.

An alternate candidate instrument for use in this unique application of analyzing hot, high pressure UF₆/UF₆-decomposition-products in an argon carrier gas is the quadrupole mass spectrometer. Reference 11 and personal communications with the author revealed considerable modifications are required, in conjunction with a molecular beam type inlet system and a liquid nitrogen cold trap to make the quadrupole mass spectrometer reasonably compatible with UF₆. The measurements reported in Ref. 11 were for on-line analysis of UF₆ in gaseous diffusion cascades. The measurements and test results indicated that the apparent high resolution of the quadrupole could not be realized with UF₆, primarily due to inadequate sensitivity and low signal-to-noise ratio. The conclusion reached was that considerable more development would be required to adapt this instrument to the isotopic analysis of UF₆. In the course of evaluation, considerable modifications were completed to the instrument, including modifications to the source structure (Monel filter rods and a nichrome source) and the ionization chamber, in addition to the molecular beam type inlet and cold trap system referenced above. From the standpoint of duty cycle, initial source life of the quadrupole, during exposure to UF₆, was limited to a few hours (analyzer pressures <10⁻⁸ torr). Although reasonably encouraging data were obtained after extensive modifications to the quadrupole system, overall performance was still considerably below that required for the intended application. Since maximum sensitivity was required, operation of the quadrupole with UF₆ required repeated adjustment of many parameters to minimize the rate of formation of UF₆ reaction products on the ion sources. At
pressures $>10^{-8}$ Torr in the main body of the analyzer these deposits formed very rapidly. In general, reproducibility of desired conditions from day-to-day was unsatisfactory. Noise was difficult to control due to changing surface conditions on the filter poles. Based on these results and the in-house experience with T.O.F. systems and the associated servicing aspects, the T.O.F. mass spectrometer was chosen for application to the PCR research effort.

A review of the literature indicated very few reports exist containing the relative mass spectral intensities for inorganic fluorine containing vapors and gases, in particular, for UF$_6$. The reason is due to problems related to corrosion and safety. One such report (Ref. 12) was the result of work done in 1974 at Los Alamos Scientific Laboratory. This report points out the difficulties associated with the corrosion/impurity aspects. The corrosion subsequently leads to contamination of the sample by volatile impurities.

Various techniques can be used for obtaining reliable detailed mass spectra of corrosive fluorine containing gases such as hot, pressurized UF$_6$. These may include elaborate passivation techniques for the surface of the various components (Ref. 13), employment of cryogenic inlet systems (Ref. 14), and use of molecular beams (Ref. 15). The scope of the present effort does not include such an extensive developmental effort at this time, since the main emphasis is on determining the feasibility and practicality of the applicable techniques. Therefore, much of the equipment was adapted with as many fluorine/UF$_6$ compatible materials available as possible.

Good quantitative analytical measurements using a mass spectrometer system in this type of application require extensive calibration procedures; this allows comparing the spectra taken under similar conditions and, in particular, with the same instrument. Based on the literature search, many of the inorganic fluorine-containing gases (heavy atomic mass) have not been standardized from the standpoint of calibration operating conditions and tabulated ion abundance levels in the mass spectra. This lack of standardization of operating conditions in reporting the spectra make ion abundance levels unreliable for quantitative analysis. The results reported in Ref. 12 present the first extensive cataloging of the ion relative abundance and sensitivities of about twenty-four fluorine-containing gases in a systematic manner. All the measurements were made using a modified Bendix T.O.F. mass spectrometer similar to that used in the tests reported herein. The inlet was constructed entirely of fluorine-compatible materials (primarily nickel and Monel with welded joints). Another subtle but important modification was the use of Kel-F material for the line connecting the molecular leak to the source. Reference 12 indicates that until these modifications were made, introduction of UF$_6$ generated many impurity peaks.
Figure 7 is a plot, assembled from some of the tabulated experimental data reported in Ref. 12, illustrating the relative sensitivity and relative abundances for UF₆. The sensitivity factor, relative to nitrogen, S (equal to 0.16 for UF₆), is defined as the ratio of the peak height of the largest peak (e.g., Intensity = 100 for m/e = 29) to the peak height of an equivalent pressure of N₂ at its largest peak, m/e = 28. The data key shown within the vertical brackets of Fig. 27 indicates the relative intensity, atomic mass, and corresponding species, respectively. These data were obtained at an ionizing voltage of 70 ev; this is approximately the same level as that employed in the current tests. Personal communication with the author of Ref. 12 again emphasized that use of high purity UF₆ (obtained from Union Carbide Corp.), the modifications described previously, and an extensive passivation procedure (details contained in Ref. 13) first using fluorine and then UF₆ resulted in the elimination of the majority of the large impurity peaks. The gases were sampled several times followed by a nitrogen purge to obtain the relative sensitivities. Reference 12 indicates that the sensitivity was found to decrease slowly with exposure to the samples, particularly for the heavy metal fluorides. This was primarily due to adsorption of compounds on the surface of the glass strip electron multiplier. Reference 12 reports the reproducibility of the relative peak heights was ±2 percent for major peaks and less for minor peaks. The impurity peaks were identified from their relative abundance patterns and subtracted from the spectra. All impurity peaks with relative abundances >0.5 (on a scale of 100) were taken into account. The most frequently observed impurities reported were N₂, O₂, and HF. These were probably introduced from air leaks and reactions with adsorbed water during manufacture, storage, and transfer.

Figure 28 is an example of the type of mass spectral relative intensities obtained from one of the many calibration tests conducted prior to connecting the T.O.F. system to the sampling probe assembly. In this particular test, 100 mm Hg of filtered (using NaF trap system) UF₆ in a 0.5L canister was topped off with 660 mm Hg of filtered argon. These tests included several samplings at the same conditions (T.O.F. unit operated at 5×10⁻⁶ mm Hg and a scan rate of 100 amu/min) followed by complete transfer line purging with argon for checking relative sensitivities. Results of the calibration tests indicated reasonably good reproducibility for the major and minor peaks. The Hg⁺ and Hg²⁺ lines observed and shown in Fig. 28 were due to the mercury used in the diffusion pump. A number of unidentified impurity peaks can be seen in Fig. 28 (e.g., m/e = 229, 155, 96, 85, 81, 77, 73, and 47). Examination of Ref. 16, which contains a comprehensive index of approximately 8000 mass spectra, did not permit positive identification. The spectral data presented in Ref. 16, consist of the six strongest peaks in each spectrum and their relative intensities, along with the name of the compound. Seven separate indexes are based on molecular weight, most intense peak, and second peak through the sixth peak. Personal communication with the author of Ref. 12, however, revealed a similar grouping of unidentified impurity peaks occurred until such time as all the modifications to the T.O.F. mass spectrometer system mentioned previously were completed. Since the scope of the present effort did not permit
these extensive modifications, these impurities were to be expected. Note that the abundances of all the ions of the UF₆ decomposition species are clearly evident in Fig. 28, with the exception of UF₆⁺ and F⁺. These would not have been expected in these tests since they have relative abundances approximately an order of magnitude less than the UF₆⁺⁺ peak (1.1 units relative intensity) shown at the atomic mass location of 157 in Fig. 28.

Figures 29 and 30 are two typical examples of the mass spectral relative intensities obtained in the 1.2 MW uranium rf plasma tests using the on-line T.O.F. mass spectrometer system shown in Fig. 10. The data in Fig. 29 are from a test with the sampling probe located in the on-axis exhaust duct directly behind the pressure water-cooled heat exchanger, as shown in Fig. 6. The data shown in Fig. 30 are from a test with the sampling probe located in the axial bypass exhaust duct. In all tests conducted, no trace of UF₆⁺⁺ (corresponding to UF₅⁺ peak) was detected in any of the measurements taken with the sampling probe located in the axial bypass exhaust duct at the centerline location. This result was also confirmed using the on-line IR absorption technique described in the previous section.

TABLE IV summarizes some of the results obtained using the T.O.F. mass spectrometer system. The data reduction used incorporated the ratio of Ar₁³⁶ to Ar₁⁴₀, since in the majority of tests conducted the magnitude of the Ar₁⁴₀ relative intensity was considerably above that of adjacent series. Also included in the data reduction was the cross section difference correction between the argon and nitrogen. TABLE IV shows that the highest concentration of UF₆ determined was of the same order as that determined using the alternate IR spectrophotometer absorption technique. This is believed to be the first time T.O.F. mass spectrometer equipment has been used for on-line measurement of hot, pressurized uranium species from the exhaust of a UF₆ plasma. These results are encouraging from the standpoint that this system represents a flexible and powerful technique for obtaining quantitative measurements of the chemical composition in different sections of the exhaust system and is also applicable to future hot UF₆/argon separator and UF₆ reprocessing system components.

TABLE II summarizes the results. The test times ranged from 2.5 to 11.2 minutes; the UF₆ injection mass flow rate ranged from 1.9x10⁻² to 6.4x10⁻² g/s. As previously discussed in the 'Tests With Porous Exhaust Duct Assembly' section, typically 0.1 to 0.2 mg of residue coating was left on the porous Monel interstage exhaust duct. This level of coating was almost undetectable by visual observation thus demonstrating the effectiveness of the porous wall technique in allowing transport of the majority of the hot UF₆/UF₆ decomposition products to a downstream location where efficient recovery and reprocessing techniques can be applied.

* < 500 ppm --- lower detectability limit of existing gas sampling/T.O.F. system.
TABLE V is an example of a complete post-test analysis conducted that corresponds to the test Case IX shown in TABLE II. In this example the total test time was 11.2 minutes. Refer to Fig. 18 for a schematic of the components examined. Figure 31 contains photographs showing the test chamber before and after this long run time test. Close observation reveals a light coating visible on the UF$_6$ injector that protrudes into the test chamber from the right endwall. A very light residue coating is also visible on the faces of both endwalls. At the specified UF$_6$ flow rate of $6.4 \times 10^{-2}$ g/s, the 11.2 minute test corresponds to a total UF$_6$ injected mass of 43 $\mu$m. Based on the post-test residue analysis, approximately 13 percent of the total UF$_6$ injected was deposited on the components upstream of the cold trap system. The majority of this was deposited on the walls of the high pressure water-cooled secondary exhaust duct (see Fig. 18). Less than 0.1 percent was deposited within the confines of the rf plasma test chamber; approximately 0.6 percent was deposited within the axial bypass exhaust duct.

Based on the results of the different diagnostic techniques employed, the CAMECA Scanning Electron Microprobe (SEM) provided much worthwhile information. This included identification of the elements present in the residue samples as well as the associated scanning electron micrographs/x-ray distributions. Figures 32 through 34 are examples of the type of information obtained for the long run test test using the SEM system. In these examples, a magnification of 500X was used. Both the electron micrographs and the corresponding x-ray distribution for the major component (U) are shown. The results shown in Fig. 32 corresponding to sample residue removed from the surface of the test chamber (UF$_6$ injector and left endwall). The back-scattered electron micrographs shown in Fig. 32a and 32c illustrate the typical topographical variations present. Figures 32b and 32d show the accompanying x-ray maps corresponding to uranium. At the magnification of 500X, the predominance of uranium, as shown by the white areas, is evident. Figure 33 shows results obtained from electron photomicrographs and x-ray maps taken of residue removed from the axial bypass exhaust duct and the interstage exhaust duct. In the case of the x-ray map for uranium, Fig. 33b illustrates the minor contribution due to uranium. As expected, the sample residue removed from the axial bypass exhaust duct was different than that removed from the on-axis exhaust duct components; the reason is attributed to the bulk temperature differences. The temperature within the axial bypass exhaust duct is considerably lower (5-10X) than that of the thru-flow exhaust. In general, a hotter exhaust combined with downstream water-cooled exhaust ducts/heat exchangers (as in the main exhaust duct system) will result in a more rapid quench effect. This manifests itself as an amorphous residue deposit on the component. Also noted were differences in the sample morphology relative to the axial location in the test component from where the particular sample was taken. This may be related to the type of axial temperature gradient present.

The presence of minor amounts of iron (Fe) and/or copper (Cu) as detected in several of the SEM post-test analyses (see Figs. 32b, 33d, 34b, and 34d) would tend to indicate some reaction with the wall material may have taken place. This was
not confirmed, however, by the IR spectrophotometer absorption and ISS/SIMS measurements or the other diagnostic techniques used. As indicated within the third column of TABLE V different complementary diagnostic techniques were employed to aid in defining the major and minor constituents. These are indicated in the fourth column of TABLE V; the minor constituent is shown within the parentheses. The far right column of TABLE V contains information on visual observations and the accompanying coating pattern observed during the post-test analysis. Because of the possibility of chemical and/or catalytic reactions between the various uranium species and the constituents (including impurities) of the exhaust duct materials, additional material reference samples were prepared and analyzed using both the IR spectrophotometer and the ISS/SIMS techniques. These included standard and anhydrous forms of CuF₂, FeF₂, FeF₃, NiF₂, and NiSIF₆. Several of these compounds possess a distinct characteristic spectrum but these absorption bands were not found in any of the post-test analyses conducted during the UF₆ rf plasma exhaust duct tests (see TABLE VIII).

To further understand the types of compounds forming on the surfaces of the various components, additional supporting tests were conducted using the ISS/SIMS technique. The IR absorption technique readily identifies the presence (qualitatively) of the UO₂F₂ but UF₄ possesses no characteristic spectrum in the 2.5 to 40 μm wavelength range. The presence of amorphous material also precludes the use of electron or x-ray diffraction techniques. Therefore, additional reference samples were prepared of the two predominant fluorides (UO₂F₂ and UF₄) and the three oxides (UO₂, UO₃, and U₃O₈) as potential contributors to possible residue coating; these were analyzed by the ISS/SIMS system. TABLE VI is a summary of available information pertinent to the several dominant oxides and fluorides of uranium. As noted in TABLE VI, the decomposition aspects of several of the compounds complicates the ability to determine what compounds may be initially formed on the walls of the test chamber compared to those determined during post-test analysis after exposure to moist air. The ISS/SIMS system provides two techniques for performing detailed chemical analyses of surfaces. Depending on the system used, the readout of the secondary ion current versus mass number leads to identification of the elements and compounds leaving the surface. Both the sputtered yield and the degree of ionization depend both on the ion being measured and on the properties of the substrate. As a consequence, reference standards are required to do quantitative analysis with the ISS and SIMS. Preliminary cataloging of these standards was initiated during this test program. To provide an indication of the type of analysis results obtained with both the ISS and SIMS instrumentation, Fig. 35 gives an example of the type of intensity versus E/E₀ (energy ratio of scattered/incident ion) profile obtained from the ISS system for a reference sample corresponding to UF₄. The locations corresponding to uranium, fluorine, oxygen, and copper are labeled on the abscissa. This information forms part of the uranium compound reference standards and diagnostic techniques at UTRC applicable for post-test characterization and quantitative identification of the residue coatings possible on the current and future test configurations.
Figure 36 shows two examples of the surface chemical analysis of some uranium compound residues removed from the wall of the interstage exhaust duct obtained using the SIMS system. These examples show the relative intensity versus the atomic mass units (AMU) (225 to 300). Figure 36a was obtained for the test case wherein the interstage exhaust duct was operated relatively hot. Figure 36b corresponds to a case where the exhaust duct operated at a relatively low temperature and the argon inlet trap system was not employed. A distinct difference in the relative intensity peak heights is noticeable, particularly at AMUs of 257, 273, and 292. Part of this difference may be attributed to the influence of contaminants in the case where the inlet trap system was not activated.

Analysis of the ISS/SIMS test results combined with the IR absorption and the other complementary measurements indicates that the residue deposited (relatively uniformly) on the walls of the exhaust duct is composed almost entirely of UO$_2$F$_2$ and UF$_6$. Based on the limited number of tests conducted, insufficient data are available at present to quantitatively determine the ratio of UF$_4$ to UO$_2$F$_2$ but preliminary analysis using the ratios of UF$_2$/UOF, UF$_3$/UF$_2$, and UF/UF$_2$ of the test results obtained in this test program would indicate a 50:50 to 70:30 breakdown appears likely. To further improve the ability to quantitatively ascertain the ratio of the uranium compounds present, considerably more reference samples would have to be prepared using different ratios of UF$_4$ and UO$_2$F$_2$ and also some with the inclusion of small percentages of the several oxide compounds. This effort was not within the scope of the present program but may be included in future work.

Refer to APPENDIX A for a complete cataloging of the IR reference sample test results. Reference 9 also contains a summary of an additional thirty reference compound standards used in the IR spectrophotometric analysis.

TABLE VII provides an overall summary of the post-test residue analyses: it also indicates the progress made to date in reducing the residue coatings that occur on the various components used in the UF$_6$ rf plasma confinement and exhaust duct tests. In general, use of upstream filter and trap systems (for both the argon and UF$_6$) has aided in eliminating some of the contaminants and subsequent residue coatings. Selecting the inlet flow conditions in the UF$_6$ rf plasma test chamber with appropriate axial bypass flow has permitted reducing the residue coating that occurs on the fused-silica tube peripheral wall. Employing Kelrez O-ring material (perfluoroelastomer) and using a sparing amount of Kel-F oil on the O-rings used for sealing the fused-silica tube peripheral wall to the endwalls has also helped in minimizing the residue deposited on the peripheral wall. The very light coating that still appears near the ends of the peripheral wall (see Fig. 14) is principally UO$_2$F$_2$. This may be attributed to the trace amounts of H$_2$O in the fused-silica tube being baked out during hot flow tests and, in turn, reacting with the UF$_6$ in the boundary to form UO$_2$F$_2$ and HF according to the reaction

\[ \text{UF}_6 + 2\text{H}_2\text{O} \rightarrow \text{UO}_2\text{F}_2 + 4\text{HF}. \]

It is also possible that the moisture consumed in this reaction is regenerated by the following reaction:

\[ \text{SiO}_2 + 4\text{HF} \rightarrow \text{SiF}_4 + 2\text{H}_2\text{O}. \]

Thus trace amounts of moisture are capable of reacting with relatively large amounts
of UF₆. To combat this, more elaborate procedures could be employed in the fused-silica tube precleaning and bakeout but the disassembly of the entire test chamber between every test with replacement of O-rings, Kel-F oil, etc. would nullify the added effort. Prior to all UF₆ rf plasma hot flow tests conducted, the fused-silica tubes were thoroughly washed with trichlorethylene and outgassed under vacuum for an approximately four hour time interval.

As shown in TABLE VII, the approximate order of magnitude reduction in residue wall coatings on the endwall assemblies for the specific configuration tested has been achieved primarily by operating the endwalls at as high a temperature as possible (≈700 K) subject to heat transfer and material limitations. The left endwall assembly (exhaust side of the test chamber) inherently operates at a slightly higher temperature (≈800 K) than the right endwall and correspondingly the associated wall coatings are less. The right endwall assembly incorporates both the UF₆ injector and the argon vortex buffer gas injectors with their associated secondary flow patterns. These secondary flow patterns in the vicinity of the endwall surface also effect the coating pattern observed (see TABLE V, Component B). Attempts to operate the left endwall assembly at still higher temperatures (≈800 K using a steam augmentation scheme) resulted in severe erosion/corrosion of the inside diameter of the endwall exhaust duct with subsequent failure of the component. Figure 37 illustrates the extremes of these erosion/corrosion aspects.

Based on the overall results of these tests, it appears that the typical milligrams of coating occurring on the left endwall assembly represent about the minimum levels obtainable using this test configuration and operating within the test conditions employed. Further reductions could be achieved by employing porous endwall assemblies and maintaining a bleed flow of argon gas through the surface in contact with the plasma. As shown in TABLE VII, post-test residue analysis of the interstage exhaust duct in the early exploratory tests revealed coatings of typically 600-800 mg. Use of reduced cooling to this component (i.e., operating at higher wall temperatures) combined with upstream injector flow augmentation has reduced these coatings by approximately a factor of 300X. Incorporating a porous Monel interstage exhaust duct assembly with argon bleed flow resulted in another approximate order of magnitude (10X) reduction in the residue wall coating. These levels of coating (i.e., hundreds of micrograms range) are nearing the practical detectibility limit of the measuring instruments and represents an extremely small fraction (≈5x10⁻⁶) of the total UF₆ flow injected into the test chamber. As indicated in TABLE VI, with the exception of the UF₆ injector assembly, the major constituents deposited (not plated -- as determined from separate emission spectroscopy measurements) on the various components were UO₂F₂ and UF₄. UO₂ was also found as a major constituent on the UF₆ injector assembly.

These results are encouraging from the standpoint of minimizing the wall coatings to relatively low levels but also in application to future tests employing batch and/or on-line UF₆ reprocessing-recirculation systems. The presence of only several major constituents each capable of reconversion back to UF₆ should aid in permitting design and development of an efficient UF₆ regeneration exhaust gas system.
REFERENCES


REFERENCES (Continued)


REFERENCES (Continued)


LIST OF SYMBOLS

AMU  Atomic mass unit, dimensionless
E/E_0  Energy ratio of scattered to incident ions, dimensionless
\( f \)  RF operating frequency, MHz
I  Intensity, arbitrary units
I_0  Incident or source intensity, arbitrary units
I/I_0  Transmission, dimensionless
\( \log_{10}(I/I_0) \)  Absorbance, dimensionless
L  Path length, cm
L  Liters
m  Particle mass, g
m/e  Atomic mass
\( \dot{m}_{\text{Ar}} \)  Argon buffer gas flow rate, g/s
\( \dot{m}_{\text{Ax}} \)  Axial bypass flow rate, g/s
\( \dot{m}_{\text{UF}_6} \)  \( \text{UF}_6 \) flow rate, g/s
P  Pressure, atm, mm Hg, or Torr
P_c  Chamber pressure, atm
Q  Power, kW
Q_R  Power radiated, kW
Q_T  Total rf discharge power, kW
R  Radius, cm
LIST OF SYMBOLS (Concluded)

<table>
<thead>
<tr>
<th>Symbol</th>
<th>Description</th>
</tr>
</thead>
<tbody>
<tr>
<td>( r )</td>
<td>Radial distance, cm</td>
</tr>
<tr>
<td>( S )</td>
<td>Sensitivity factor, dimensionless</td>
</tr>
<tr>
<td>( T )</td>
<td>Temperature, deg K</td>
</tr>
<tr>
<td>( T_w )</td>
<td>Wall temperature, deg K</td>
</tr>
<tr>
<td>( t )</td>
<td>Time, minutes (m) or seconds (s)</td>
</tr>
<tr>
<td>( kV )</td>
<td>Voltage, kilovolts</td>
</tr>
<tr>
<td>( V_\phi )</td>
<td>Swirl velocity, m/s</td>
</tr>
<tr>
<td>( V_z )</td>
<td>Axial velocity, m/s</td>
</tr>
<tr>
<td>( W )</td>
<td>Weight of residue material, mg</td>
</tr>
<tr>
<td>( \chi )</td>
<td>Mole fraction, dimensionless</td>
</tr>
<tr>
<td>( Z )</td>
<td>Axial length, m</td>
</tr>
<tr>
<td>( \lambda )</td>
<td>Wavelength, nm or microns</td>
</tr>
<tr>
<td>( \Delta \lambda )</td>
<td>Wavelength band, nm</td>
</tr>
</tbody>
</table>
APPENDIX A: SUPPORTING INFORMATION ON THE CORROSION/CONTAMINATION ASPECTS OF UF₆ AND ASSOCIATED REACTANT SPECIES

To aid in the analysis of the present and future tests, continued supporting research was conducted and information cataloged pertinent to UF₆ and other candidate reactant uranium compounds and derivatives, the compatibility with different materials, and the associated corrosion/contamination aspects. This APPENDIX highlights some of this information.

With respect to basic properties, UF₆ is, at atmospheric conditions, a crystallized translucid solid (orthorhombic structure). It is unique in being the only uranium compound that has the property of subliming, under normal pressure, at about 329 K. Refer to Refs. 17 and 18 for detailed discussions of the properties of UF₆ and the other related intermediate fluorides. Reference 19 contains a complete discussion of the thermochemistry of the gaseous uranium fluorides.

The complexity of the U-O-F system and the associated properties of UF₆, particularly at elevated temperatures and pressures, make a complete understanding of the corrosion aspects extremely difficult. This is because any reaction, whatever the mechanism, will permit the metal coming into contact with the UF₆ to also react with the fluorine or reactive fluoride from the UF₆. References 21, 22, and 23 discuss the aspects of fluorine technology, fluorination, and fluorine corrosion. Intermediate fluorides may also be present within the gas-metal interface. These intermediates may or may not participate in the actual corrosion reaction, but they will react with the gaseous phase to yield equilibrium products at the particular temperature and pressure conditions. Another complication is that any trace of moisture as an impurity can generate hydrofluoric acid which can also significantly modify the corrosion rate.

Several topics were of interest related to the type of tests conducted in this research program. The first was the question of impurity and contamination of the UF₆ and other reacting gases and materials. Second was the question of the accuracy of the published property data (much being in disagreement between different investigators), and third was the area of corrosion relative to high temperature, high pressure operation with UF₆ and its decomposition/reactant constituents.

From the standpoint of impurities, a detailed assay of the UF₆ used in the tests reported herein is documented in Ref. 9. Throughout the course of the test program it became obvious that it was extremely important to try and eliminate as much of the moisture, oxygen, and HF present as possible. UF₆ reacts vigorously with H₂O according to the equation: UF₆ + 2H₂O → UO₂F₂ + 4HF. The incorporation of the traps and getters as used on the supply systems throughout the test program aided in reducing these impurities to tolerable levels. Filtering the as-received
UF₆ through an anhydrous NaF powder trap was effective in reducing the amount of HF contained in the UF₆. There is still a need for additional improvements in the area of contamination.

The chemical state of the metal surface is also of importance with respect to the level of attack by the UF₆. For example, any trace of organic matter (e.g., fingerprints deposited during disassembly/assembly) are a site for preferential attack. The adsorbed water will lead to an immediate decomposition of UF₆ together with the attendant formation of HF. It may be possible to significantly reduce the corrosion by using mechanical polishing of the machined metal surface of the test component. However, a mechanically-polished surface may still contain physical imperfections. Electrolytic polishing would be an alternate scheme for possible elimination of the crystalline layer in question. The presence of thin surface oxides on the initial metal surface may also influence the corrosion rate depending upon the composition, structure, and thickness of the oxide layers.

TABLE VI shows a comparison of several of the physical and chemical properties of the various oxide and fluoride compounds of uranium that are relevant to this research program. As noted in TABLE VI, the decomposition of several of the compounds complicates the ability to determine what compounds may be initially formed on the walls of the test components during testing as opposed to those determined during the post-test analysis using different diagnostic techniques.

Additional reference data were also acquired during this test program using the IR absorption spectrophotometer system. TABLE VIII is a summary of the material reference samples that were examined and cataloged. The majority display a distinct absorption spectrum between 2-40 μm. Should any of these compounds form on the surface of the test components in future tests, a positive identification will be possible. Also included for reference are several of the copper, iron, and nickel fluorides which may form as a surface layer during fluorine passivation conditions.

Before an assessment can be made of potential corrosive situations, information is required on the composition of the constituents at the operating temperatures and pressures in question. Figure 38 is an example of the type of data that have been generated and cataloged. This figure shows the equilibrium composition of a UF₆/argon mixture as a function of temperature. The total pressure of 2 atm is typical of the pressures employed in actual hot flow UF₆ rf plasma tests. Three different UF₆ partial pressures, ranging from 1 Torr to 10⁻² Torr are included. The temperature range in the actual experiments extended from room temperature to levels approaching 10⁴ K within the rf plasma test chamber. In the UF₆ feeder system, typical temperatures were about 450 K, while in the primary exhaust ducts a radial temperature profile was present (as illustrated in Fig. 20) which ranged from about 350 K at the wall to greater than 3000 K on-axis.
The actual UF₆ corrosion process is characterized by the reaction between an anhydrous gaseous phase and a solid phase. This process is comparable to the dry oxidation of metals. Refer to Refs. 24, 25, and 26 for a detailed discussion of UF₆ attack on metals and metallic fluorides. During some of the early tests with the UF₆ transfer system, post-test examination revealed some etch pits after the deposits were removed. Attack by UF₆ can proceed by micropitting; this may be related to the well known fact that halogens in solution also cause pitting. Based on the similarity to dry oxidation depth growth curves, the growth in depth would be expected to follow parabolic time laws. In future experiments, the Secondary Ion Mass Spectrometer (SIMS) could be used to analyze the formation of these fluoride monolayers. The corrosion layers obtained will depend primarily on the nature of the metal (or alloy), its structure and the associated temperature regime. Preliminary observations of some of the test components revealed a powdery layer adjacent to the metal. During other inspections, a somewhat crystalline layer was observed, while in some of the higher temperature regions, a crust-like coating was occasionally present.

At relatively high temperatures (>500 K) and in some locations the surface of the metal appeared to be covered only by the metal fluoride. If this layer is in the powder form, then it would no longer provide a protective coating. As far as the intermediate uranium fluorides are concerned, they most likely will occur on the highly cooled surfaces of the experiment. This can be attributed to their considerable vapor pressure, even at relatively high temperatures.

The key problem that was present throughout the test program was the occasional clogging of the UF₆ shutoff and flow control valves (see Fig. 5). In spite of strict precleaning, handling, and assembly, plugging of the valves did occur several times throughout the test series. The cleaning procedure employed an acid-flush technique. The component was first cleaned with 0.1 N HCl solution, followed by trichlorethylene, and then a heated bakeout (≈500 K). This was followed by outgassing under vacuum conditions for approximately four hours. Other parts of the UF₆ canister and transfer system showed signs of partial attack by UF₆; this included a failure of the nickel tube adjacent to the exit of the UF₆ boiler. The tube contained a 90 deg bend with associated thin wall and residual stresses induced by the stretch bending. The failure was a combination of erosion/corrosion occurring in the vicinity of the high stresses. X-ray and IR spectrophotometer analysis of the material from this and other components of the system (including the plugged valve assembly) indicated UF₄, UO₂F₂, UO₂, and occasionally a fourth unidentified (amorphous structure) compound may be present. After removal of the material, some areas showed signs of micropitting. Under a UF₆ environment, very small (<0.1 μm deep) micropits can start to appear at relatively low temperature (<400 K). Other points of preferential attack are surface defects, such as grinding marks, scratches, etc., or phases out of solid solution. At higher temperatures, the grain boundaries are subject to attack. Reference 26 points out that some of the impurities in the material itself can also be preferentially attacked (e.g., in the steels it is the
sulfides which are most reactive). Oxide inclusions are attacked at higher temperatures along with the silicates. In the case of stainless steels, the attack occurs on sulfides, carbides, and oxides. In copper, Cu_{2}O is preferentially attacked. With Monel (of the type used in the porous wall duct), the titanium carbonnitrides and magnesium oxides or sulfides are preferentially attacked.

In addition to the temperature and exposure-time factors, the progress of UF_{6} corrosion may be influenced by other factors which are external to the metal. These would include purity of the gas phase and pressure. At low and moderate temperatures, pressure is not that significant as reactions are dominated by the diffusion phenomena in the corrosion layers. At higher temperatures pressure becomes more important through the volatility of the reaction products in equilibrium with UF_{6}. As mentioned previously, the purity of the gas phase is quite difficult to control since there are always some impurities in the UF_{6} (particularly HF). Even small quantities of HF can effect the corrosion rate in a significant manner.

The details of UF_{6} corrosion aspects are probably most critical when viewed from the safety aspect. Reliable data must be made available to permit judicious selection of the material (and/or combinations of materials) to use for the various test components in order to minimize the corrosion problem and subsequent failure of the component. Due to the unavailability of experimental data on the corrosion aspects of hot, pressurized UF_{6}, some preliminary information has been accumulated. Some of this may be applicable to future high temperature, high pressure UF_{6} plasma experiments. Reference 9 contains an example of corrosion rate data for different materials as a function of temperature. The preferred use of nickel or Monel was obvious when compared to other materials. For example, at 1000 K, there is greater than four orders of magnitude (10^{4}X) difference between the rate of corrosion of 316 stainless steel compared to nickel. In the regime of UF_{6} pressures of about 0.3 atm, typical rates of corrosion are 10^{2} \mu m/hr for stainless steels and 10^{-2} \mu m/hr for nickel. The progress of the reaction is generally revealed by a weight gain of the material in question. To establish maximum test time safety criteria, measurements could also be made of the depth of the corrosion as a function of test conditions.

Where possible, the majority of the key components exposed to UF_{6} and used in the experiments have incorporated nickel or Monel material. A survey of the literature (Refs. 27, 28, and 29) and personal communications with UTRC Materials Laboratory personnel revealed the most corrosion resistant materials to be nickel or nickel alloys (including NiAl). Alternate materials may also be required since nickel possesses a relatively high capture cross section for thermal neutrons, thereby restricting its application in full-scale PCRs to perhaps a thin plating.

A search of the literature revealed very little quantitative experimental data on the UF_{6}-Ni system. Reference 27 indicates that if proper prepassivation techniques are employed, the reaction of UF_{6} with Ni can be significantly reduced, particularly at high temperatures ( \approx 1000 K). Similarly, Ref. 24 indicates that UF_{6} does not react with the metallic difluorides (assumed low temperature regime).
At the high temperatures and pressures of interest, the UF₆, F₂, HF, and most of the lower fluorides formed from the dissociation of UF₆ (see Fig. 38) are all relatively corrosive. Since F₂, F, and some HF may be present, they will be the more reactive species. Therefore, the materials used in the different test components should also be capable of long term survival under the fluorine environment.

Most of the research on fluorine corrosion of different materials has been done at relatively high fluorine pressures. The experiments reported herein and the actual designs for full scale plasma core reactors may operate at considerably lower pressures of fluorine. Lower rates of fluorine attack on the materials should accompany the lower pressures.

A considerable amount of information is available in the literature (see Refs. 28 and 30) on the corrosion of nickel by fluorine. The F₂ occurring from the thermal dissociation of the UF₆ while the HF occurs due to the H₂O contamination reaction with UF₆. Reference 28 contains data on the influence of temperature on the corrosion of Ni by F₂. An example is shown below.

<table>
<thead>
<tr>
<th>Temp. (°K)</th>
<th>PF₂ (atm)</th>
<th>Test Time (min)</th>
<th>Estimated Loss of Metallic Nickel for 1 Year Long Exposure (µ)</th>
</tr>
</thead>
<tbody>
<tr>
<td>357</td>
<td>0.92</td>
<td>110</td>
<td>0.21</td>
</tr>
<tr>
<td>773</td>
<td>0.92</td>
<td>1800</td>
<td>3.0</td>
</tr>
<tr>
<td>913</td>
<td>1.0</td>
<td>150</td>
<td>140</td>
</tr>
<tr>
<td>1083</td>
<td>1.0</td>
<td>100</td>
<td>310</td>
</tr>
</tbody>
</table>

Note that increasing the temperature from 357 K to 773 K results in an approximate factor of 15X increase in the corrosion. Extending the temperature to 1083 K results in another two orders of magnitude increase in loss of nickel. The mechanism of the corrosion resistance of nickel to fluorine is one of passivation of the nickel surfaces by NiF₂. The fluorination rate of nickel appears to be sensitive to small amounts of impurities. Most impurities or alloying materials used with nickel (e.g., carbon, iron, sulfur, silicon) degrade the corrosion resistance to fluorine. Figure 39 illustrates the effect of temperature and fluorine on nickel material structural strength. Electrolytic grade nickel 200 starts to exhibit a complete loss in its yield strength at temperatures of about 1200 K; this is also the onset of extensive chemical attack.

Reference 31 contains the results of T.O.F. mass spectrometer measurements made of the reaction of polycrystalline nickel with fluorine. The temperature range was 900–1600 K, the corresponding fluorine pressures were between 10⁻⁷ and 10⁻⁴ Torr. The major products were gaseous NiF₂, NiF, and fluorine. These were formed rapidly on the surface at rates linear with the fluorine pressure. NiF
was found to be present on the surfaces over the entire temperature range and desorbed above 1373 K. NiF₂ formation and desorption were found to be important between 900-1600 K. The rate-limiting step in the formation of NiF₂ is probably dissociation of fluorine on the surface.

Based on the above information, it is obvious that considerably more data will be required over a wide range of operating conditions to fully document the possible corrosive effects that long time exposure to high temperature, high pressure UF₆, fluorine, HF, and the intermediate fluorides can have on the various materials proposed for use as components in continued experimental tests. In the limited tests conducted in this program, the periodic post-test inspection of different components has only provided a qualitative indication of the degree of corrosion attack that occurred.
APPENDIX B: SUPPORTING ANALYSIS OF HEAT AND MASS TRANSFER ASPECTS OF SWIRLING HOT FLOW WITHIN A POROUS DUCT WITH BLEED FLOW AUGMENTATION

One of the key components used in the UF6 rf plasma exhaust gas tests reported in this research program was the porous Monel interstage exhaust duct assembly. Prior engineering analyses and experimental studies have been conducted on the heat transfer from a plasma or high temperature axially flowing gas to the confining walls of a water-cooled tubular test section (Refs. 32, 33, and 34). Additional work has also been published on the aspects of using a porous surface to thermally protect it from an adjacent hot fluid flow (Refs. 35 and 36). This method is known as transpiration cooling. Extensive studies have also been made of both the fluid dynamic and heat transfer effects of transpiration cooling by injecting either the same or a foreign gas through a porous surface into an external flow. These have included both laminar and turbulent boundary layers, in subsonic as well as supersonic flows, with zero as well as nonzero pressure gradients in the direction of flow. (Refer to Refs. 37 and 38 for extensive bibliographies.) Numerous analytical solutions have also been obtained for laminar flow in tubes, between parallel plane walls, and in annuli for transpiration injection through porous walls. In contrast, essentially nothing has been published for the case of swirl flow within a duct with the addition of transpiration injection. Therefore a preliminary supporting analysis was conducted* using a modified existing computer code developed in the Fluid Dynamics Laboratory of UTRC (Ref. 39). Because of the complexity of the problem, only argon gas was considered for both the main carrier gas and the transpiring coolant. Also not included in this preliminary analysis was the additional complex uranium chemistry and possible homo-/heterogeneous reactions and catalytic effects that may occur.

The objective of this analysis was to establish some initial trends which might aid in selecting the flow parameters and configurations to be used in forthcoming UF6 rf plasma experiments. Experimental test results reported herein have already indicated the feasibility of employing a 5-μm nominal pore size Monel duct to aid in reducing the uranium compound coatings deposited on the walls of the primary exhaust duct. Another attractive feature of employing a porous duct scheme is that it also permits the addition of different concentrations of fluorine gas (F2) to the diluent argon carrier gas as an aid in converting some of the uranium compounds back to UF6 while still in the flowing gaseous state. Considerable more analysis and experiments will be required to permit selection of a system that has optimized flow conditions for maximum UF6 regeneration while simultaneously minimizing the wall coating effect.

*Analysis conducted by O. L. Anderson.
Required inputs to the program were: geometry, physical dimensions of the exhaust duct, gas properties, total inlet mass flow rate, inlet axial and swirl velocity parameters (velocity profiles $V\phi$ and $V_z$), inlet temperature profile, wall temperature, and total transpiration mass flow rate (uniformly injected).

The program calculated: the radial temperature and velocity profiles at different axial locations, the heat flux to the wall, the bulk Reynolds and Nusselt numbers, and additional information on the boundary layer parameters. For the purpose of this APPENDIX, it will suffice to include several of the key results and trends determined for future comparison of these to the type of actual hot flow test results obtained in continuing UF$_6$ rf plasma exhaust system experiments.

Figure 40 is an example of several of the basic test configurations investigated. The first case shown is representative of the type of solid wall, water-cooled interstage exhaust duct assembly used in several of the actual UF$_6$ rf plasma hot flow tests with swirl. The significant dimensions and test conditions were selected as being representative of those used in the actual hot flow UF$_6$ rf plasma tests. The second case shown is geometrically similar to the first, but the solid wall has been replaced with a porous wall to permit uniform transpiration injection along the entire length, $Z$. The third case shown in Fig. 40 is actually a composite of the prior two (i.e., a porous duct has been located immediately downstream of the cooled, solid wall assembly). This geometry closely approximates that used in the group of long run time hot flow test series conducted in this portion of the research program and, therefore, is the case of most relevance.

Due to previously discussed difficulties with corrosion/erosion of the thermocouples used to measure the temperatures at several selected locations within the exhaust duct, the temperature profile was estimated and extrapolated from the limited data available for a low power test case.

For estimating the velocity profiles, a DISA anemometer system and a Thermo-Systems Inc. hot-film probe (2-mil-dia) transducer was used in several of the exploratory tests to measure the approximate isothermal velocity profiles of the argon buffer gas exiting the interstage exhaust duct. Equipment availability and test schedule did not permit extensive measurements, therefore, as with the temperature determinations, additional estimates were also included to account for the influence of higher temperatures.

Figure 41 is a composite plot illustrating the effect of increasing only the transpiration bleed flow rate through the porous duct on the velocity and temperature distributions for the last case shown in Fig. 40 (refer to TABLE II (last case) and Fig. 15 for details of test configuration, significant dimensions, and test conditions). The assumed wall temperature ($T_w$) was 700 K. The highest transpiration injection bleed flow rate shown (4.3 g/s) corresponds to the actual test condition used in several of the UF$_6$ rf plasma hot flow tests. It can be seen in Fig. 41c
that increasing the bleed flow rate to this level has resulted in a definite leveling off of the temperature from about the $r/R = 0.75$ position to the wall location ($r/R = 1.0$). The effect of the bleed flow on minimizing the wall coating was demonstrated in the experimental results; thus it appears that the diffusion of the uranium compounds toward the wall can indeed be counter-balanced by the radial transpiration injection of the argon bleed gas through the porous wall.

If required in the future, additional refinements could be made to this operational computer program to permit a detailed parametric analysis of the combined effects of varying wall temperature, radial flow rate, and vortex swirl/velocity parameters. This would permit a complete optimization of the test conditions required, within the physical constraints allowable, for minimizing the wall coating due to uranium compound deposition.
<table>
<thead>
<tr>
<th>TABLE I</th>
</tr>
</thead>
<tbody>
<tr>
<td>SUMMARY OF PHYSICAL AND MECHANICAL PROPERTY DATA FOR MONEL 400</td>
</tr>
</tbody>
</table>

<table>
<thead>
<tr>
<th>COMPOSITION, %</th>
<th>Ni 66.5, Cu 31.5, Fe 1.25, Mn 1, Si 0.25, C 0.15, S 0.12</th>
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</thead>
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<tr>
<td>PHYSICAL PROPERTIES</td>
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<td>Density, lb/in.³</td>
<td>0.319</td>
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<tr>
<td>Melting Range, F</td>
<td>2370-2460</td>
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<tr>
<td>Permeability (70 F, H=200 oersted)</td>
<td>-</td>
</tr>
<tr>
<td>Annealed</td>
<td>-</td>
</tr>
<tr>
<td>Age Hardened</td>
<td>-</td>
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<tr>
<td>Specific Heat (70 F), BTU/lb/°F</td>
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<tr>
<td>Coefficient of Thermal Exp., in./in./°F</td>
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<tr>
<td>70-200 F</td>
<td>$7.7 \times 10^{-6}$</td>
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<tr>
<td>70-1000 F</td>
<td>$9.1 \times 10^{-6}$</td>
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<tr>
<td>Thermal Conductivity, BTU/ft²/hr/hr/°F</td>
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<tr>
<td>70 F</td>
<td>12.6</td>
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<td>1000 F</td>
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<td>Electrical Resistivity, ohms/cmf</td>
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<tr>
<td>70 F</td>
<td>307</td>
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<tr>
<td>1000 F</td>
<td>367</td>
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<tr>
<td>MECHANICAL PROPERTIES</td>
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<tr>
<td>Modulus of Elasticity (70 F), psi</td>
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<tr>
<td>Tension</td>
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<tr>
<td>Torsion</td>
<td>$10 \times 10^6$</td>
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<tr>
<td>Ult Ten Str, 1000 psi</td>
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<tr>
<td>70 F</td>
<td>70-1000</td>
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<td>500 F</td>
<td>77</td>
</tr>
<tr>
<td>1000 F</td>
<td>45</td>
</tr>
<tr>
<td>Yld Str (0.2% offset), 1000 psi</td>
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<tr>
<td>70 F</td>
<td>25-100</td>
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<tr>
<td>500 F</td>
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<td>1000 F</td>
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<td>Elongation (in 2 in.), %</td>
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<td>70 F</td>
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<td>500 F</td>
<td>50</td>
</tr>
<tr>
<td>1000 F</td>
<td>30</td>
</tr>
<tr>
<td>Hardness (70 F), Brinell</td>
<td>110-241</td>
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</tbody>
</table>
### TABLE II

**SUMMARY OF UF₆ RF PLASMA TESTS CONDUCTED IN 1.2 MW RF INDUCTION HEATER USING POROUS MONEL EXHAUST DUCT CONFIGURATION**

See Fig. 15 for Details of Test Configuration

<table>
<thead>
<tr>
<th>Test Case</th>
<th>RF Operating Frequency (f-MHz)</th>
<th>Argon Buffer Gas Flow Rate (ha Ar-g/s)</th>
<th>Axial Bypass Flow Rate (ha AX-g/s)</th>
<th>Chamber Pressure (Pc-atm)</th>
<th>RF Discharge Power, QRF (kW)</th>
<th>Discharge Diameter (cm)</th>
<th>Porous Duct Bleed Flow Rate (ha D-g/s)</th>
<th>UF₆ Injection Mass Flow Rate (ha UF₆-g/s)</th>
<th>Inlet Mass Ratio (UF₆/Ar)</th>
<th>Total Test Time (t-min)</th>
<th>Weight of Residue Deposited on Porous Duct (Wp-mg)</th>
</tr>
</thead>
<tbody>
<tr>
<td>I</td>
<td>5.4325</td>
<td>3.20</td>
<td>0.65</td>
<td>2.7</td>
<td>49</td>
<td>3.0</td>
<td>3.60</td>
<td>0.038</td>
<td>0.012</td>
<td>2.5</td>
<td>0.229</td>
</tr>
<tr>
<td>II</td>
<td>5.4260</td>
<td>2.85</td>
<td>1.12</td>
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<td>37</td>
<td>3.1</td>
<td>4.27</td>
<td>0.019</td>
<td>0.007</td>
<td>4.2</td>
<td>0.072</td>
</tr>
<tr>
<td>III</td>
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<td>3.04</td>
<td>1.15</td>
<td>3.1</td>
<td>47</td>
<td>3.1</td>
<td>3.22</td>
<td>0.028</td>
<td>0.009</td>
<td>6.0</td>
<td>0.295</td>
</tr>
<tr>
<td>IV</td>
<td>5.4304</td>
<td>3.04</td>
<td>1.12</td>
<td>3.1</td>
<td>48</td>
<td>3.2</td>
<td>4.27</td>
<td>0.034</td>
<td>0.011</td>
<td>6.0</td>
<td>0.132</td>
</tr>
<tr>
<td>V</td>
<td>5.4320</td>
<td>3.04</td>
<td>0.90</td>
<td>2.7</td>
<td>48</td>
<td>3.05</td>
<td>4.27</td>
<td>0.022</td>
<td>0.007</td>
<td>10.2</td>
<td>0.210</td>
</tr>
<tr>
<td>VI</td>
<td>5.42.5</td>
<td>2.95</td>
<td>1.07</td>
<td>2.4</td>
<td>41</td>
<td>3.25</td>
<td>4.27</td>
<td>0.027</td>
<td>0.009</td>
<td>5.6</td>
<td>0.188</td>
</tr>
<tr>
<td>VII</td>
<td>5.4332</td>
<td>3.10</td>
<td>0.82</td>
<td>2.8</td>
<td>47</td>
<td>3.0</td>
<td>4.27</td>
<td>0.060</td>
<td>0.023</td>
<td>2.5</td>
<td>0.110</td>
</tr>
<tr>
<td>VIII</td>
<td>5.4310</td>
<td>3.04</td>
<td>0.85</td>
<td>3.4</td>
<td>51</td>
<td>3.2</td>
<td>5.45</td>
<td>0.062</td>
<td>0.020</td>
<td>5.3</td>
<td>0.151</td>
</tr>
<tr>
<td>IX</td>
<td>5.4288</td>
<td>3.04</td>
<td>1.13</td>
<td>2.6</td>
<td>43</td>
<td>3.15</td>
<td>4.27</td>
<td>0.064</td>
<td>0.021</td>
<td>11.2</td>
<td>0.207</td>
</tr>
</tbody>
</table>
TABLE III
EXAMPLE OF TEST RESULTS FROM ON-LINE IR SPECTROPHOTOMETER ABSORPTION MEASUREMENTS

See Fig. 6 for Schematic of Sampling System -- Sampling Probe Located at Position B Downstream of Low Pressure Heat Exchanger Assembly -- 623 cm\(^{-1}\) Wavenumber Used Operating Frequency, \(f_0\), = 5.4362 MHz, \(P_c = 1.3\) atm, IR Cell Pressure \(\approx 1.0\) atm See Fig. 26 for Example of Absorption Measurements Corresponding to A, B, C

<table>
<thead>
<tr>
<th>Discharge Power (Q_T) (kW)</th>
<th>Sampling Test Time (t), (sec)</th>
<th>Argon Buffer Gas Flowrate (\dot{m}_{Ar}) (g/s)</th>
<th>Axial Bypass Flowrate (\dot{m}_{Ax}) (g/s)</th>
<th>(UF_6) Injection Flowrate (\dot{m}_{UF_6}) (g/s)</th>
<th>Mass Ratio ((UF_6/Ar))</th>
<th>Dye Laser Reference Beam Transmission ((I/I_0)) (\lambda = 591.54) nm</th>
<th>Partial Pressure of (UF_6) in Kel-F IR Cell, (P_{UF_6}) (mm Hg)</th>
<th>(^{19}F_6) Concentration (ppm)</th>
</tr>
</thead>
<tbody>
<tr>
<td>A</td>
<td>24</td>
<td>50</td>
<td>3.04</td>
<td>1.03</td>
<td>0.008</td>
<td>0.003</td>
<td>0.86</td>
<td>0.07</td>
</tr>
<tr>
<td>B</td>
<td>36</td>
<td>27</td>
<td>3.04</td>
<td>1.03</td>
<td>0.019</td>
<td>0.006</td>
<td>0.69</td>
<td>0.19</td>
</tr>
<tr>
<td>C</td>
<td>44</td>
<td>24</td>
<td>3.04</td>
<td>1.03</td>
<td>0.039</td>
<td>0.013</td>
<td>0.44</td>
<td>1.02</td>
</tr>
</tbody>
</table>
### TABLE IV

**EXAMPLE OF RESULTS OBTAINED USING THE T.O.F. MASS SPECTROSCOPIC SYSTEM INTEGRATED ON-LINE WITH THE UF₆ RF P.F. ASMA EXHAUST SAMPLING TESTS**

See Fig. 10 for Photograph of System
See Fig. 6 for Schematic of Exhaust Gas Sampling System
See Figs. 29 and 30 for Examples of Mass Spectral Intensity Outputs

<p>| | | | | | | | |</p>
<table>
<thead>
<tr>
<th></th>
<th></th>
<th></th>
<th></th>
<th></th>
<th></th>
<th></th>
<th></th>
</tr>
</thead>
<tbody>
<tr>
<td></td>
<td>$f_0$ (kHz)</td>
<td>$Q_T$ (kPa·m³/h)</td>
<td>$P_c$ (g/s)</td>
<td>$\dot{n}_{Ar}$ (g/s)</td>
<td>$\dot{n}_{AX}$ (g/s)</td>
<td>$\dot{n}_{UF_6}$ (g/s)</td>
<td>Mass Ratio UF₆/Ar</td>
</tr>
<tr>
<td>A</td>
<td>5.420</td>
<td>48</td>
<td>2.48</td>
<td>2.86</td>
<td>0.6</td>
<td>0.024</td>
<td>0.008</td>
</tr>
<tr>
<td>B</td>
<td>5.4199</td>
<td>45</td>
<td>2.20</td>
<td>2.86</td>
<td>0.58</td>
<td>0.014</td>
<td>0.005</td>
</tr>
<tr>
<td>C</td>
<td>5.4230</td>
<td>43</td>
<td>2.35</td>
<td>2.86</td>
<td>1.03</td>
<td>0.014</td>
<td>0.005</td>
</tr>
</tbody>
</table>

**Measured UF₆ Concentration (ppm)**
TABLE V

SUMMARY OF POST-TEST ANALYSIS CONDUCTED AFTER LONG RUN TIME UF₆ RF PLASMA TEST

See TABLE II, Case IX for Corresponding Test Conditions
See Fig. 18 for Schematic of Components Examined

<table>
<thead>
<tr>
<th>Component</th>
<th>Weight of Residue (mg)</th>
<th>Diagnostic Techniques Employed</th>
<th>Constituents</th>
<th>Visual Observation/Coating Pattern</th>
</tr>
</thead>
<tbody>
<tr>
<td>A-UF₆ Injector</td>
<td>17.5</td>
<td>SEM</td>
<td>U(0,F,Cu)</td>
<td>Light brown, grey coating in vicinity of tip, mist green coating near face of endwall, clean copper on face of tip exposed to plasma.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺</td>
<td></td>
</tr>
<tr>
<td>B-Right Endwall Assembly</td>
<td>6.6</td>
<td>SEM</td>
<td>U(F,Cu)</td>
<td>White mist coating on argon vortex injectors, light brown/green/white coating extending to approximately mid-radius, inner portion more green/brown.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺ Trace UF₆ + amorphous material.</td>
<td></td>
</tr>
<tr>
<td></td>
<td></td>
<td>Electron Diffraction</td>
<td></td>
<td></td>
</tr>
<tr>
<td>C-Placed-Silica Peripheral Wall</td>
<td>9.2</td>
<td>SEM</td>
<td>U(0,Si,F)</td>
<td>Trace of white misty residue near left end in area adjacent to O-ring, similar pattern at extreme right end with additional evidence of swirl pattern.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺</td>
<td></td>
</tr>
<tr>
<td></td>
<td></td>
<td>Profilometer</td>
<td></td>
<td></td>
</tr>
<tr>
<td></td>
<td></td>
<td>Electron Diffraction</td>
<td></td>
<td></td>
</tr>
<tr>
<td>D-Left Endwall Assembly</td>
<td>1.4</td>
<td>SEM</td>
<td>U(F,0)</td>
<td>Essentially clean, also true for region inside endwall exhaust duct.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺</td>
<td></td>
</tr>
<tr>
<td></td>
<td></td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>E-Axial Bypass Exhaust Duct</td>
<td>240.3</td>
<td>SEM</td>
<td>O,F(U)</td>
<td>Whitish/pale green very light coating uniformly deposited on inside diameter.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺</td>
<td></td>
</tr>
<tr>
<td>F-Interstage Exhaust Duct</td>
<td>11.7</td>
<td>SEM</td>
<td>U₂O₅⁺ Fe(Cu,Si,F)</td>
<td>Whitish colored light coating uniformly deposited over entire inside diameter.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺</td>
<td></td>
</tr>
<tr>
<td></td>
<td></td>
<td>Wet Chem.</td>
<td></td>
<td></td>
</tr>
<tr>
<td></td>
<td></td>
<td>SANS/ISS</td>
<td></td>
<td></td>
</tr>
<tr>
<td>G-Foam Monel Duct</td>
<td>0.2</td>
<td>SEM</td>
<td>U₂O₅⁺ Fe(F,0)</td>
<td>Barely visible whitish mist coating at extreme downstream end of duct.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>IR</td>
<td>U₂O₅⁺</td>
<td>Majority U trace of reactant wall material.</td>
</tr>
<tr>
<td></td>
<td></td>
<td>Emission Spectroscopy</td>
<td></td>
<td></td>
</tr>
<tr>
<td>H-High Pressure Water-Cooled Secondary Exhaust Duct</td>
<td>5490.</td>
<td>SEM</td>
<td>U₂O₅⁺ Fe(F,0) trace Cu</td>
<td>Mist green coating deposited relatively uniformly on inside diameter.</td>
</tr>
</tbody>
</table>
### TABLE VI

**Comparison of Several Physical and Chemical Properties of Various Oxide and Fluoride Compounds of Uranium**

<table>
<thead>
<tr>
<th>Element/Component</th>
<th>Color</th>
<th>Stability to Moist Air at Room-Temp.</th>
<th>M.P. (°C)</th>
<th>B.P. (°C)</th>
<th>Solubility in H₂O (Hot/Cold)</th>
</tr>
</thead>
<tbody>
<tr>
<td><strong>U</strong></td>
<td>Bright silver (prior to tarnishing in air)</td>
<td>+H₂O [\rightarrow] UO₂ &lt;200°C</td>
<td>1132</td>
<td>3818</td>
<td>No</td>
</tr>
<tr>
<td><strong>UO₂</strong></td>
<td>Brown-Blue</td>
<td>Stable</td>
<td>2500</td>
<td></td>
<td>No</td>
</tr>
<tr>
<td><strong>UO₃</strong></td>
<td>Yellow-Red</td>
<td>Stable (Decomposes)</td>
<td></td>
<td></td>
<td>No</td>
</tr>
<tr>
<td><strong>U₃O₈</strong></td>
<td>Olive Green-Black</td>
<td>Stable (Decomposes)</td>
<td></td>
<td></td>
<td>No</td>
</tr>
<tr>
<td><strong>UF₃</strong></td>
<td>Viole Red-Black</td>
<td>Unstable (Decomposes at &gt;1000)</td>
<td></td>
<td></td>
<td>Slightly soluble (Decomposes)</td>
</tr>
<tr>
<td><strong>UF₄</strong></td>
<td>Green</td>
<td>Stable</td>
<td>960</td>
<td>No Reliable Data Available</td>
<td>Very slightly Soluble (≈100 mg/l)</td>
</tr>
<tr>
<td><strong>UF₅</strong></td>
<td>White</td>
<td>+H₂O [\rightarrow] UO₂⁺² + UF₄</td>
<td></td>
<td></td>
<td>Decomposes</td>
</tr>
<tr>
<td><strong>U₂F₂</strong></td>
<td>Black</td>
<td>+H₂O [\rightarrow] UO₂⁺² + UF₄</td>
<td></td>
<td></td>
<td>Decomposes</td>
</tr>
<tr>
<td><strong>UO₂F₂</strong></td>
<td>Pale Yellowish-White</td>
<td>Depends on Preparation 1) low temp. prep. → hygroscopic 2) high temp. hydro-fluorination → no deliquescence</td>
<td>Decomposes (&gt;120)</td>
<td></td>
<td>Yes</td>
</tr>
<tr>
<td>Component</td>
<td>Early Tests (Including Exploratory)</td>
<td>Tests To Date</td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>---------------------------------</td>
<td>-------------------------------------</td>
<td>---------------</td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td></td>
<td>Residue Weight (mg)</td>
<td>Major Constituent</td>
<td>Residue Weight (mg)</td>
<td>Major Constituent</td>
<td></td>
</tr>
<tr>
<td>Fused-Silica Peripheral Wall</td>
<td>50-600</td>
<td>UO₂F₂, (trace UF₄), UO₂, γUO₂, O-ring decomposition products</td>
<td>4-30</td>
<td>UO₂F₂, (trace UF₄)</td>
<td></td>
</tr>
<tr>
<td>Left Endwall</td>
<td>25-100</td>
<td>UO₂F₂, UF₄</td>
<td>0.1-3</td>
<td>UO₂F₂, UF₄</td>
<td></td>
</tr>
<tr>
<td>Right Endwall</td>
<td>90-200</td>
<td>UO₂F₂, UF₄</td>
<td>4-20</td>
<td>UO₂F₂, UF₄</td>
<td></td>
</tr>
<tr>
<td>UF₆ Injector</td>
<td>200-400</td>
<td>UO₂F₂, UF₄, UO₂, αUO₂, unidentified compound, (trace Cu)</td>
<td>10-50</td>
<td>UO₂F₂, UF₄, UO₂</td>
<td></td>
</tr>
<tr>
<td>Axial Bypass Exhaust Duct</td>
<td>—</td>
<td>UO₂F₂, UF₄, (trace U₃O₈)</td>
<td>100-300</td>
<td>UO₂F₂, UF₄</td>
<td></td>
</tr>
<tr>
<td>Interstage Exhaust Duct</td>
<td>600-800</td>
<td>UO₂F₂, UF₄, (trace U₃O₈)</td>
<td>7-250</td>
<td>UO₂F₂, UF₄</td>
<td></td>
</tr>
<tr>
<td>Interstage Exhaust Duct Flow</td>
<td>—</td>
<td>—</td>
<td>0.15-2.5</td>
<td>UO₂F₂, UF₄</td>
<td></td>
</tr>
<tr>
<td>Augmentation</td>
<td>—</td>
<td>—</td>
<td>0.07-0.3</td>
<td>UO₂F₂, UF₄</td>
<td></td>
</tr>
</tbody>
</table>

Average Test Time 3 minutes (range 1-11.2 minutes)
# TABLE VIII

**SUMMARY OF KEY MATERIAL REFERENCE SAMPLES USED IN IR SPECTROPHOTOMETRIC ANALYSIS**

(Refer to TABLE VI of Ref. 9 for additional list of cataloged reference samples.)

<table>
<thead>
<tr>
<th>Sample</th>
<th>Available</th>
<th>IR Spectrum Completed</th>
<th>Displays Distinguishable Spectrum</th>
</tr>
</thead>
<tbody>
<tr>
<td>KBr</td>
<td>Yes</td>
<td>Yes</td>
<td>Standard Blank – No</td>
</tr>
<tr>
<td>KeI-F Oil</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>UO&lt;sub&gt;2&lt;/sub&gt;</td>
<td>Yes</td>
<td>Yes</td>
<td>No</td>
</tr>
<tr>
<td>UO&lt;sub&gt;3&lt;/sub&gt;-amorphous</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>UO&lt;sub&gt;4&lt;/sub&gt;</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>U&lt;sub&gt;2&lt;/sub&gt;O&lt;sub&gt;8&lt;/sub&gt;</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>UO&lt;sub&gt;2&lt;/sub&gt;F&lt;sub&gt;2&lt;/sub&gt;(UO&lt;sub&gt;2&lt;/sub&gt;2&lt;sup&gt;+&lt;/sup&gt;)</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>UO&lt;sub&gt;2&lt;/sub&gt;::nH&lt;sub&gt;2&lt;/sub&gt;O&lt;sub&gt;n&lt;/sub&gt;(n=3,6)</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>USi&lt;sub&gt;2&lt;/sub&gt;</td>
<td>Yes</td>
<td>Yes</td>
<td>No</td>
</tr>
<tr>
<td>CuF&lt;sub&gt;2&lt;/sub&gt; anhydrous</td>
<td>Yes</td>
<td>Yes</td>
<td>? – highly reactive</td>
</tr>
<tr>
<td>CuF&lt;sub&gt;2&lt;/sub&gt;::2H&lt;sub&gt;2&lt;/sub&gt;O</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes-weak-reactive</td>
</tr>
<tr>
<td>FeF&lt;sub&gt;2&lt;/sub&gt; anhydrous</td>
<td>Yes</td>
<td>Yes</td>
<td>No</td>
</tr>
<tr>
<td>FeF&lt;sub&gt;3&lt;/sub&gt;::3H&lt;sub&gt;2&lt;/sub&gt;O</td>
<td>Yes</td>
<td>Yes</td>
<td>No</td>
</tr>
<tr>
<td>FeF&lt;sub&gt;3&lt;/sub&gt; anhydrous</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes-weak</td>
</tr>
<tr>
<td>NiF&lt;sub&gt;2&lt;/sub&gt;::4H&lt;sub&gt;2&lt;/sub&gt;O</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes-weak</td>
</tr>
<tr>
<td>NiF&lt;sub&gt;2&lt;/sub&gt;-anhydrous</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes-weak</td>
</tr>
<tr>
<td>NiSiF&lt;sub&gt;6&lt;/sub&gt;::6H&lt;sub&gt;2&lt;/sub&gt;O</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes-weak</td>
</tr>
<tr>
<td>UF&lt;sub&gt;6&lt;/sub&gt;</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>UF&lt;sub&gt;5&lt;/sub&gt;</td>
<td>No</td>
<td>No</td>
<td>–</td>
</tr>
<tr>
<td>UF&lt;sub&gt;4&lt;/sub&gt;</td>
<td>Yes</td>
<td>Yes</td>
<td>No</td>
</tr>
<tr>
<td>Silicon O-ring decomposition products</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
<tr>
<td>Kalrez O-ring decomposition products</td>
<td>Yes</td>
<td>Yes</td>
<td>Yes</td>
</tr>
</tbody>
</table>

58
PLASMA CORE REACTOR UNIT CELL CONFIGURATION

WORKING FLUID CHANNELS CONTAINING PARTICLES, GRAPHITE FINS OR OPAQUE GASES

ARGON BUFFER GAS INJECTOR

REFLECTIVE LINER

MODERATOR

INTERNALLY COOLED TRANSPARENT WALL

LINER COOLANT CHANNEL

FUEL REGION

0.50 M

AXIAL BYPASS

ARGON BUFFER GAS

TRANSPARENT WALL

FUEL REGION

4.35 M

ON-AXIS EXHAUST

SECTION A–A
FIG. 2

SCHEMATIC OF ARGON/UF₆ SEPARATION AND RECIRCULATION SYSTEM FOR PCR UNIT CELL CONFIGURATION

SEE FIG. 1 FOR UNIT CELL CONFIGURATION

ARGON BYPASS

UF₆ CONDENSER/SEPARATOR

UF₆ HEATER

UF₆ PUMP

UF₆ SUPPLY

ARGON BUFFER GAS IN

ARGON SUPPLY

ARGON BUFFER GAS OUT

ARGON HEATER

ARGON PUMP

PCR UNIT CELL

LIQUID UF₆

LIQUID UF₆

CHEMICAL TREATMENT SEPARATOR SYSTEM
SKETCH OF BASIC TEST CHAMBER CONFIGURATION USED IN UF₆ RF PLASMA TESTS

(SEE FIG. 3 FOR PHOTOGRAPH OF TEST CHAMBER CONFIGURATION INSTALLED IN 1.2MW RF INDUCTION HEATER TEST TANK)

FUSED SILICA TUBES
RF WORK COILS
ARGON VORTEX INJECTORS
UF₆ INJECTORS

AXIAL BYPASS EXHAUST

5.7CM
10CM

NOT TO SCALE!
SCHEMATIC OF UF₆ EXHAUST GAS SAMPLING SYSTEM USED IN BOTH IR SPECTROPHOTOMETER ABSORPTION AND T.O.F. MASS SPECTROMETER MEASUREMENTS
SCHEMATIC OF IR SPECTROPHOTOMETER SYSTEM USED IN UF₆ RF PLASMA EXHAUST GAS AND POST TEST RESIDUE ANALYSIS

SEE FIG 18 FOR PHOTOGRAPH OF SYSTEM
PHOTOGRAPH OF KEL-F CELL AS USED IN EXHAUST GAS IR ABSORPTION MEASUREMENTS
FIG. 11

SCHEMATIC REPRESENTATION OF A TIME-OF-FLIGHT (TOF) MASS SPECTROMETER

IONIZATION SOURCE

IONIZING ELECTRON BEAM

IONIZATION

IONIZED MOLECULES

ELECTRIC FIELD FREE DRIFT TUBE

ION-SELECTIVE ANIONIZER

(SEPARATES IONS)

SOURCE (PRODUCES IONS)

DETECTOR (COLLECTS IONS)

PRESSURE

FLOW OF GAS MOLECULES

FROM SAMPLING NOSE

PULSED ACCELERATING POTENTIAL

INSTRUMENT OUTPUT

m₁ m₂ m₃ m₄

t₁ t₂ t₃ t₄ (μSEC)

V

m₁ m₂ m₃ m₄

(1 - v_Wv) - s_Yv

Pc

FIGURE 11
SKETCH OF CROSS-SECTION OF UF₆ RF PLASMA TEST CHAMBER AND TRANSPARATION INJECTION EXHAUST DUCT
PHOTOGRAPHS OF POROUS MONEL INTERSTAGE EXHAUST DUCT AND DIFFERENT POROSITY TUBES USED IN EXPLORATORY TESTS
POST TEST PHOTOPHOTOGRAPH OF TEST CHAMBER AND POROUS MONEL INTERSTAGE EXHAUST DUCT SYSTEM
USED IN UF₆ RF PLASMA EXHAUST GAS TESTS
SCHEMATIC OF COMPONENTS EXAMINED IN POST TEST ANALYSIS OF LONG RUN TIME TEST

SEE TABLE II FOR RANGE OF TEST CONDITIONS

TO DOWNSTREAM COLD TRAPS, LOW PRESSURE HEAT EXCHANGER AND NEUTRALIZING TRAP ON LABORATORY ROOF

HIGH PRESSURE WATER COOLED EXHAUST DUCT

POROUS MONEL DUCT

WATER COOLED INTERSTAGE EXHAUST DUCT

ANNULAR AXIAL BYPASS EXHAUST DUCT

FUSED SILICA PERIPHERAL WALL

UF₆ INJECTOR

LEFT END WALL ASSEMBLY

RIGHT END WALL ASSEMBLY

PERIPHERAL WALL, SO₂ (ALSO SOURCE OF O₂)

POSSIBLE SPECIES WITHIN PLASMA TEST CHAMBER

UF₆, UF₅, UF₄
UF₃, U, U⁺⁺⁺
U⁺⁺, U⁺⁺⁺⁺, F,
F⁻, F₂, UF₂, UF₂
UO₆

POSSIBLE INLET CONTAMINANT

HF
O₂
H₂O
HYDROCARBONS
FIG. 20

EXAMPLE OF MEASURED RADIAL TEMPERATURE PROFILES ACROSS INLET AND EXIT LOCATION OF INTERSTAGE EXHAUST DUCT ASSEMBLY

SEE FIG. 12 FOR SCHEMATIC OF CONFIGURATION; w/W Rh T.C.'s EMPLOYED IN THESE MEASUREMENTS
ARGON ONLY LOW POWER RF PLASMA TEST CASE

KEY
△ INLET LOCATION
○ EXIT LOCATION

REGION OF THERMOCOUPLE FAILURE
MEASURED VARIATION IN INTERSTAGE EXHAUST DUCT RESIDUE WALL COATING WITH COOLANT FLOW RATE

SEE FIG. 12 FOR SKETCH OF BASIC TEST CONFIGURATION

TEST CONDITIONS APPROXIMATELY CONSTANT IN ALL TESTS:

\[ f_s = 5.4359 \text{ MHz} \]
\[ Q_f = 45 \text{ kw} \]
\[ \dot{m}_{AV} = 3.04 \text{ g/s} \]
\[ \dot{m}_{AX} = 0.57 \text{ g/s} \]
\[ P = 1.75 \text{ ATM} \]
\[ \dot{m}_{UF_6} = 0.018 \text{ g/s} \]
\[ t = 3 \text{ MIN} \]

KEY:

- \( \Box \) \( \text{H}_2O/O_2 \) FILTER/TRAP NOT ACTIVATED
- \( \triangle \) \( \text{H}_2O/O_2 \) FILTER/TRAP IN USE

POST TEST RESIDUE in mg DEPOSITED ON:

EXHAUST (LEFT) ENDWALL

INJECTION (RIGHT) ENDWALL

UF_6 INJECTOR

ENDWALL COOLANT FLOW RATE = 0.096 l/s

UF_6 INJECTOR COOLANT FLOW RATE = 0.087 l/s

STEAM AUGMENTATION TEMP. = 365 K

INTERSTAGE EXHAUST DUCT COOLING WATER FLOW RATE, \( \dot{m}_F \) /s
FIG. 22

MEASURED VARIATION IN INTERSTAGE EXHAUST DUCT RESIDUE WALL COATING WITH DILUENT GAS INJECTOR FLOW RATE

SEE FIG. 12 FOR SKETCH OF TEST CONFIGURATION
SEE FIG. 14 FOR PHOTOGRAPH OF TEST CONFIGURATION

![Graph showing the measured variation in residue wall coating with diluent gas injector flow rate. The graph includes a key with different test conditions represented by various symbols. The key describes the test conditions for each symbol.

KEY:
- ○ REF. TEST CONDITION WITH STANDARD FLANGE ASSEMBLY
- △ SWIRL INJECTOR ASSEMBLY
- □ CO-AXIAL INJECTOR ASSEMBLY
- ◇ RADIAL INJECTOR ASSEMBLY

RANGE OF TEST CONDITIONS:
- $Q_T = 39-46$ kW
- $f_D = 5.4300-5.4340$ MHz
- $P_c = 1.4-1.9$ ATM
- $\dot{m}_{AR} = 3-3.1$ g/s
- $\dot{m}_{AX} = 0.8$ g/s
- $\dot{m}_{UF6} = 0.015-0.025$ g/s
- $t = 2.9-3.5$ MIN.

ARGON FLOW RATE THRU DILUENT INJECTOR, $\dot{m}_D$ g/s

APPROXIMATE TEST CORRIDOR
EXAMPLE OF POURED MONEL EXHAUST DUCT RESIDUE WALL COATING VERSUS TEST TIME

SEEN FIG. 16 FOR DETAILS OF TEST CONFIGURATION
SEE TABLE 1 FOR CORRESPONDING TEST CONDITIONS

NOTES TESTS AT APPROXIMATELY CONSTANT UF6 MASS FLOW RATE

WEIGHT OF POST TEST RESIDUE COLLECTED FROM

FIG. 23
INFRARED SPECTRUM OF UF₆

GASEOUS STATE
ROOM TEMPERATURE
10 CM CELL LENGTH

DISPERSING ELEMENT
REF. 10

\{ \begin{align*}
\text{NaCl PRISM} & : 8.5-15 \ \mu \text{m} \\
\text{KBr PRISM} & : 15-20 \ \mu \text{m}
\end{align*} \}

WAVELENGTH - \mu \text{m}

PERCENT TRANSMISSION

WAVENUMBER - \text{cm}^{-1}
EXAMPLES OF IR SPECTROPHOTOMETRIC ABSORPTION MEASUREMENTS

PERKIN ELMER MODEL 457
PATH LENGTH=10CM

a) EVACUATED (10μM) FUSED SILICA CELL WITH AgCl WINDOWS

WAVELENGTH - μM

H₂O IN REF. BEAM
HYDRO-CARBON IMPURITY IN CELL
CO₂ IN REF. BEAM
H₂O IN REF. BEAM
CO₂ IN REF. BEAM

b) FUSED SILICA CELL WITH AgCl WINDOWS FILLED WITH 0.5 GMS OF FILTERED UF₆

WAVELENGTH - μM

UF₆

676 cm⁻¹
623 cm⁻¹

SiF₄

CO₂ REF.
H₂O REF.

83
EXAMPLE OF ON-LINE IR SPECTROPHOTOMETRIC ABSORPTION MEASUREMENTS

SEE FIG. 6 FOR SCHEMATIC OF SAMPLING SYSTEM
SEE FIG. 8 FOR PHOTOGRAPH OF TEST CONFIGURATION
PERKIN ELMER MODEL 457 — PATH LENGTH 10 — CM
623 cm⁻¹ WAVELENGTH USED
SEE TABLE III FOR SUMMARY OF TEST CONDITIONS

FIG. 26
MASS SPECTRAL RELATIVE INTENSITIY OF UF₆
MEASURED ON TOF MASS SPECTROMETER AT AN IONIZING POTENTIAL OF 70 ev. REF [12]

Sensitivity factor relative to nitrogen, S = 0.18

Key:
- Relative intensity
- Atomic mass
- Species

Intensity, I - Arbitrary units

Atomic mass - m/e

UF₆⁺ 333
UF₅⁺ 314
UF₄⁺ 28.2
UF₃⁺ 26.3
UF₂⁺ 296
UF⁺ 267
UF₂⁺ 6.3
UF⁺ 5.2
UF₂⁺ 147.5
UF⁺ 128.5
UF₂⁺ 5.7
UF⁺ 4.6
UF₂⁺ 3.2
UF⁺ 1.9
UF₂⁺ 119
UF⁺ 138
UF₂⁺ 157
UF⁺ 6.5
UF₂⁺ 238
UF⁺ 8.5
UF₂⁺ 18.5
UF⁺ 100.0
EXAMPLE OF MASS SPECTRAL RELATIVE INTENSITIES OF UF₆/AR MIXTURE AS MEASURED WITH TOF MASS SPECTROMETER SYSTEM AND USED IN CALIBRATIONS OF UF₆ RF PLASMA TESTS

SEE FIG. 2 FOR SCHEMATIC OF EXHAUST GAS SAMPLING SYSTEM
SEE FIG. 10 FOR PHOTOGRAPH OF EQUIPMENT

FIG. 28

ATOMIC MASS - m/e

KEY

- RELATIVE INTENSITY
- ATOMIC MASS
- SPECIES

NOTE DASH INDICATES SPECIES YET TO BE IDENTIFIED

Hg⁺

2.1 3.8 5.2 4.0 5.8 2.5
198 199 200 201 202 204

298 238 257 276 295 314

7.5 (UF₆⁺)
EXAMPLE OF MASS SPECTRAL RELATIVE INTENSITIES OBTAINED IN UF₆ RF PLASMA TESTS USING ON-LINE TOF MASS SPECTROMETER SYSTEM

SAMPLING PROBE LOCATED IN ON-AXIS EXHAUST DUCT (DOWNSTREAM LOCATION B – SEE FIG. B)
SEE TABLE III FOR SUMMARY OF TEST CONDITIONS

KEY
RELATIVE INTENSITY
ATOMIC MASS
SPECIES

NOTE: DASH INDICATES SPECIES YET TO BE IDENTIFIED

FIG. 29
EXAMPLE OF MASS SPECTRAL RELATIVE INTENSITIES OBTAINED IN UF₆ RF PLASMA TESTS USING ON-LINE TOF MASS SPECTROMETER SYSTEM

SAMPLING PROBE LOCATED IN AXIAL BYPASS EXHAUST DUCT (DOWNSHIFT LOCATION C - SEE FIG. 8)

SEE TABLE IV FOR SUMMARY OF TEST CONDITIONS

KEY

{ RELATIVE INTENSITY
{ ATOMIC MASS
{ SPECIES

FIG. 30
FIG. 31

PHOTOGRAPHS OF TEST CHAMBER USED IN LONG RUN TIME TESTS WITH UF₆ RF PLASMA

A: BEFORE

B: AFTER
ELECTRON PHOTOMICROGRAPHS AND X-RAY MAPS OF A SAMPLE RESIDUE FROM SURFACE OF TEST CHAMBER AFTER LONG RUN TIME UF₆ RF PLASMA TEST

MAG 500 X

a) UF₆ INJECTOR BACKSCATTERED ELECTRON MICROGRAPH

b) UF₆ INJECTOR X-RAY SHOWING URANIUM, MAJOR MINOR F, O, Cu

c) LEFT ENDWALL BACKSCATTERED ELECTRON MICROGRAPH

d) LEFT ENDWALL X-RAY SHOWING URANIUM, MAJOR MINOR F, O
ELECTRON PHOTOMICROGRAPHS AND X-RAY MAPS OF A SAMPLE RESIDUE FROM SURFACE OF EXHAUST DUCT SYSTEM AFTER LONG RUN TIME UF6 RF PLASMA TEST

MAG 50,000

1. AXIAL BYPASS EXHAUST DUCT ELECTRON MICROGRAPH

2. INTERSTAGE EXHAUST DUCT ELECTRON MICROGRAPH

3. AXIAL BYPASS EXHAUST DUCT X-RAY SHOWING URANIUM: MINOR MAJOR F.O.

4. INTERSTAGE EXHAUST DUCT X-RAY SHOWING URANIUM: MAJOR MINOR, O.F.F., TRACE CuS.
Electron photomicrographs and X-ray maps of a sample residue from surface of exhaust duct system after long run time UF₆ RF plasma test.

1. Porous Monel exhaust duct backscattered electron micrograph.
2. Porous Monel exhaust duct X-ray showing uranium-major minor F,O, Fe trace Cu,Zn.
3. High pressure water cooled exhaust duct backscattered electron micrograph.
4. High pressure water cooled exhaust duct X-ray showing uranium-major minor F,O trace Cu.
EXAMPLE OF SURFACE CHEMICAL ANALYSIS OF UF₄ STANDARD REFERENCE USING ION SCATTERING SPECTROMETER (ISS)
EXAMPLES OF SURFACE CHEMICAL ANALYSIS OF URANIUM COMPOUND RESIDUE USING SECONDARY ION MASS SPECTROMETER (SIMS)

a) RESIDUE SAMPLE FROM WALL OF EXHAUST DUCT (HIGH TEMPERATURE OPERATION) AFTER TEST WITH PURE UF₆ INJECTION

b) RESIDUE SAMPLE FROM WALL OF EXHAUST DUCT (LOW TEMPERATURE OPERATION) AFTER TEST WITH PURE UF₆ INJECTION AND ARGON INLET FILTER TRAP USED.
COMPOSITION OF UF₆/ARGON MIXTURE AS A FUNCTION OF TEMPERATURE
EFFECT OF TEMPERATURE AND FLUORINE ON NICKEL MATERIAL PROPERTIES
EXAMPLE OF SEVERAL BASIC CONFIGURATIONS USED IN INTERSTAGE EXHAUST DUCT ANALYSIS

a) COOLED SOLID WALL EXHAUST DUCT WITH SWIRL - NO TRANSPIRATION INJECTION

b) POROUS DUCT - WITH SWIRL AND TRANSPIRATION INJECTION

c) COMBINATION OF THE ABOVE; SOLID WALL EXHAUST DUCT FOLLOWED BY POROUS DUCT - WITH SWIRL AND TRANSPIRATION INJECTION
COMPOSITE PLOTS SHOWING EFFECT OF INCREASING BLEED FLOW RATE THROUGH POROUS MONEL DUCT ON EXIT AXIAL AND SWIRL VELOCITY AND EXIT TEMPERATURE DISTRIBUTIONS

a) EFFECT OF POROUS DUCT BLEED FLOW RATE ON EXIT SWIRL VELOCITY

b) EFFECT OF POROUS DUCT BLEED FLOW RATE ON EXIT AXIAL VELOCITY

c) EFFECT OF POROUS DUCT BLEED FLOW RATE ON EXIT TEMPERATURE